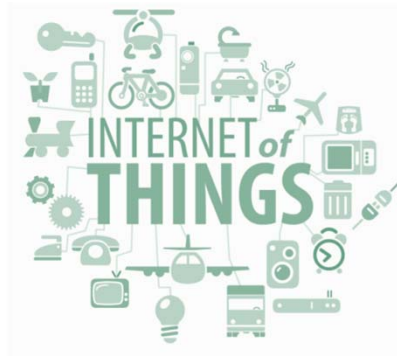

Ultra-Low Power Design Approaches for IoT

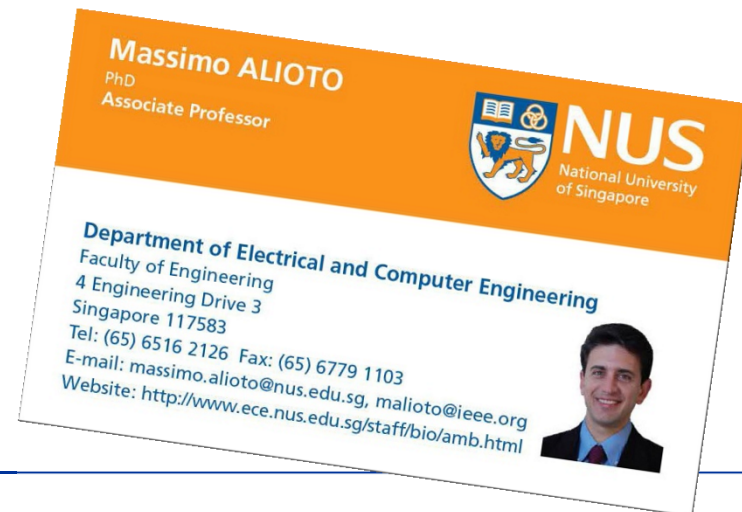


Massimo Alioto



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Green IC group

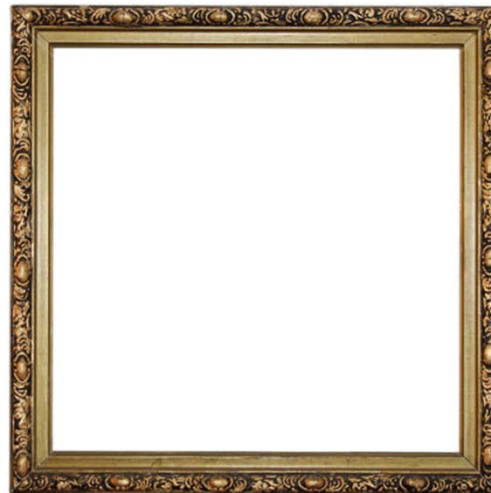
Green IC 



Outline

- ◆ IoT: the context
- ◆ Ultra-low voltage operation
- ◆ Design Issues and Solutions at Ultra-Low Voltages: Performance
 - ◆ performance
 - ◆ leakage
 - ◆ variations and resiliency
- ◆ Conclusions

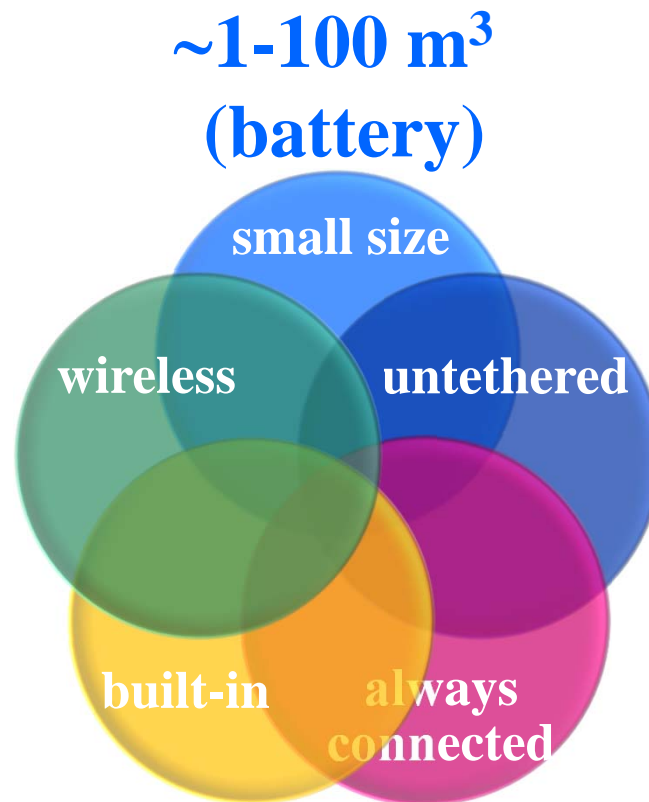
Internet of Things: The Context



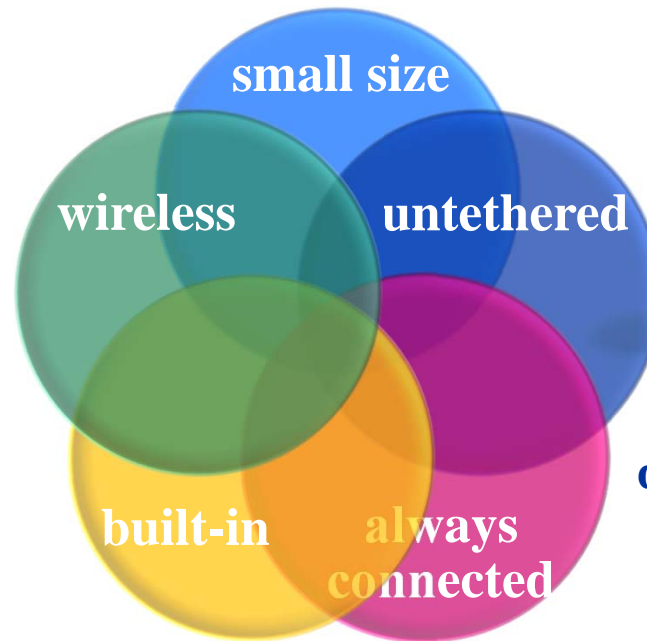
◆ Specific features of nodes for IoT



◆ Specific features of nodes for IoT



◆ Specific features of nodes for IoT



**self-powered
(limited power)**



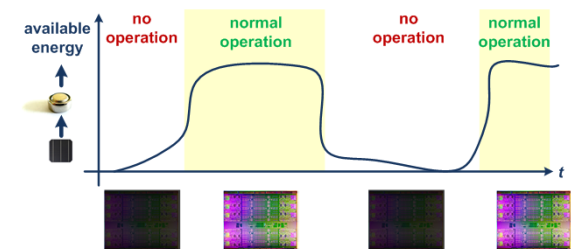
μ Ws (perpetual)



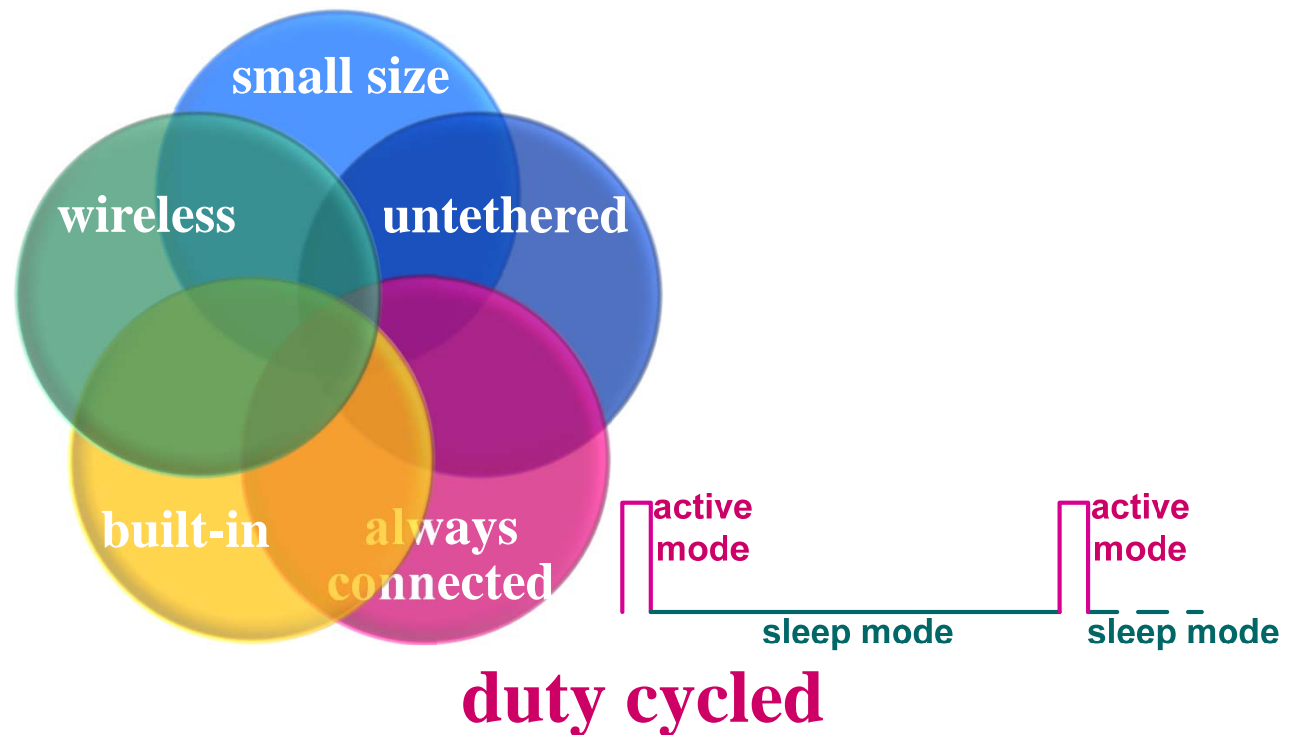
100 nW (10 yrs)

40 μ W (1 week)

dark silicon in time dimension



◆ Specific features of nodes for IoT



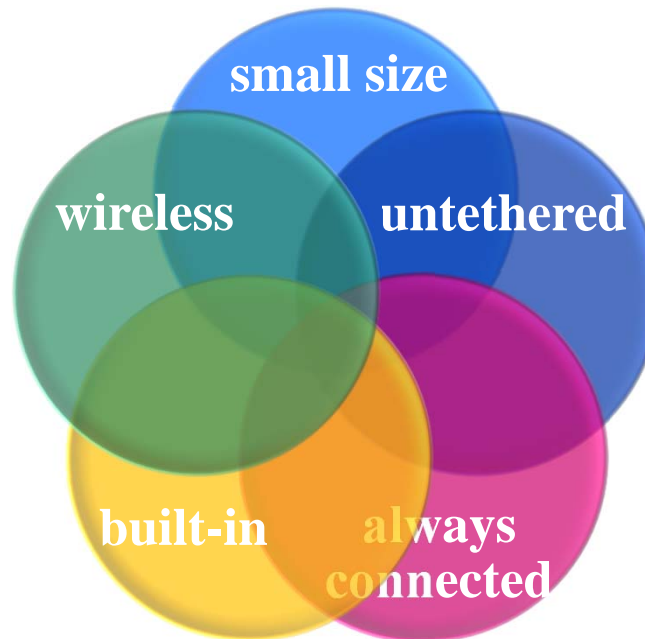
◆ Specific features of nodes for IoT

computation
repetitive

- leverage specialized HW

- real time: scalable
performance is needed

- data logging: less
performance, but memory cost



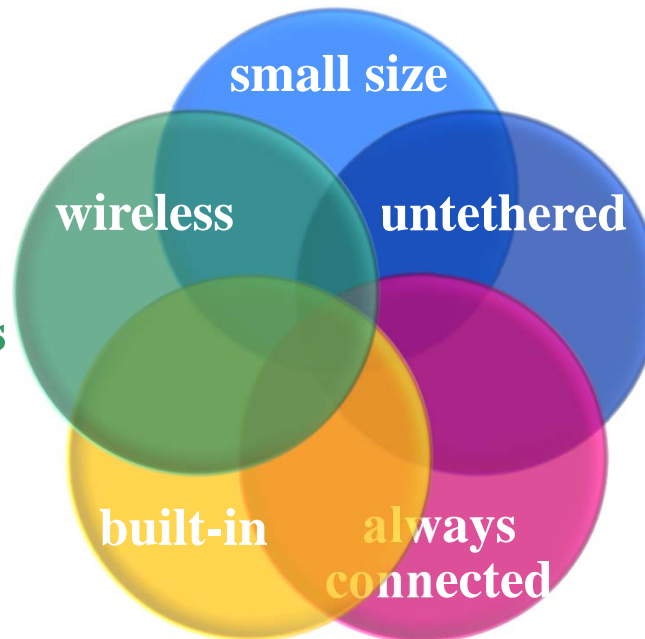
◆ Specific features of nodes for IoT

communication

computation vs

communication tradeoff

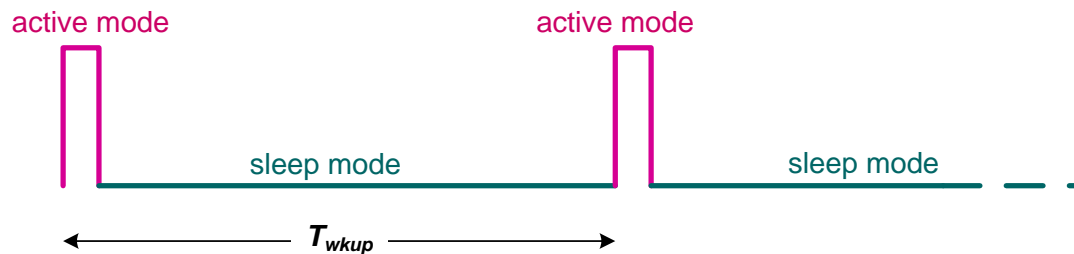
- data representation
(compressive sensing,
compression)
- limit TX to critical events
or significant changes
(critical event monitoring)



Power vs Energy

◆ Duty cycled systems with limited power

- ◆ active only periodically (or on demand) for a short time



- ◆ partition into **always-on** block (timers, retentive memory) and **duty cycled** blocks (all others, active 0.1-1% of the time)

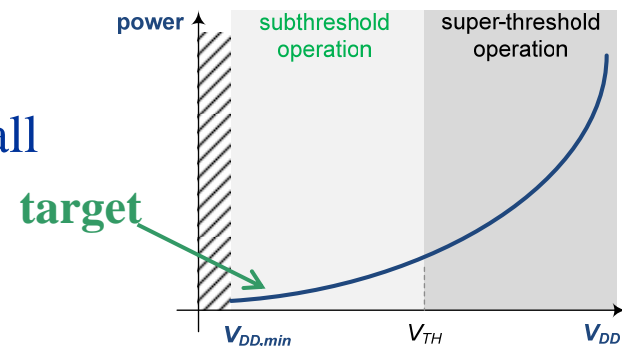
$$P_{avg} = P_{always-on} + (P_{sleep} + E_{active} / T_{wkup})$$

- ◆ $P_{sleep} \neq 0$ if duty cycled block is power gated
- ◆ $P_{sleep} = 0$ if on-chip regulator is shut down

[RJA12] M. Alioto, et Al., “Active RFID: A Perpetual Wireless Communications Platform for Sensors,” *ESSCIRC 2012*

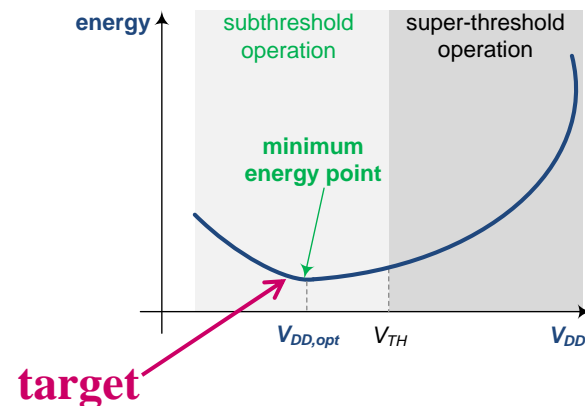
◆ **minimum power** is the goal for **always-on** block

- ◆ minimize power, essentially leakage (dynamic power very small – little active and slow)



◆ **minimum energy** per operation is the goal for **duty-cycled** blocks

- ◆ minimize energy per operation (dynamic + leakage energy)
- ◆ $1/X$ duty cycling increases energy budget by X



➔ in both cases, **ultra-low voltage operation is absolutely needed**

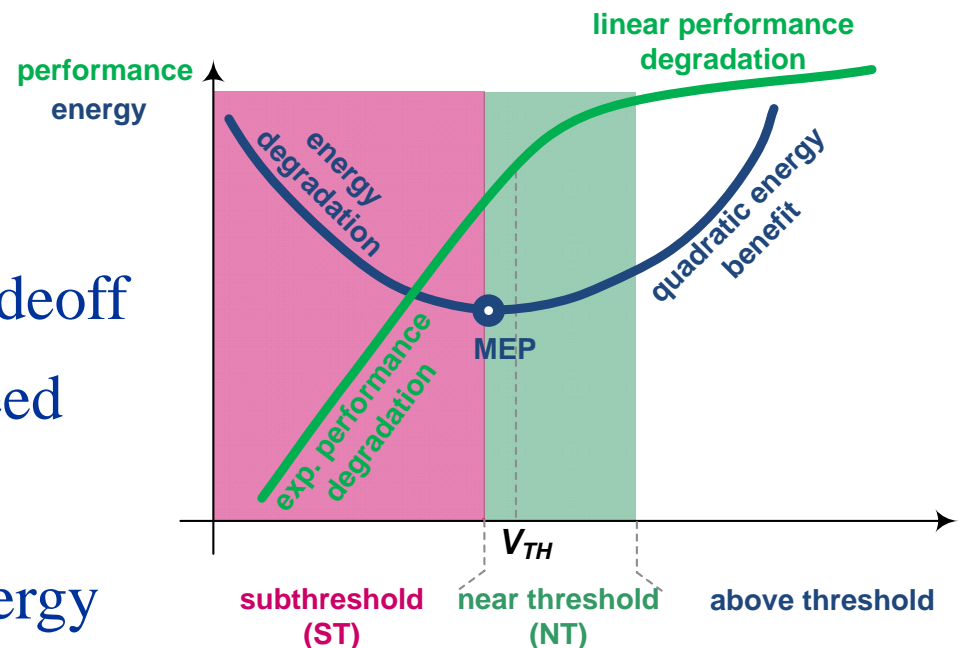
Ultra-Low Voltage Operation

Operation at Ultra-Low Voltages (ULV)

- ◆ Voltage scaling is a powerful knob to improve energy efficiency
 - ◆ quadratic benefit, if dynamic energy CV^2 dominates
 - ◆ performance degradation

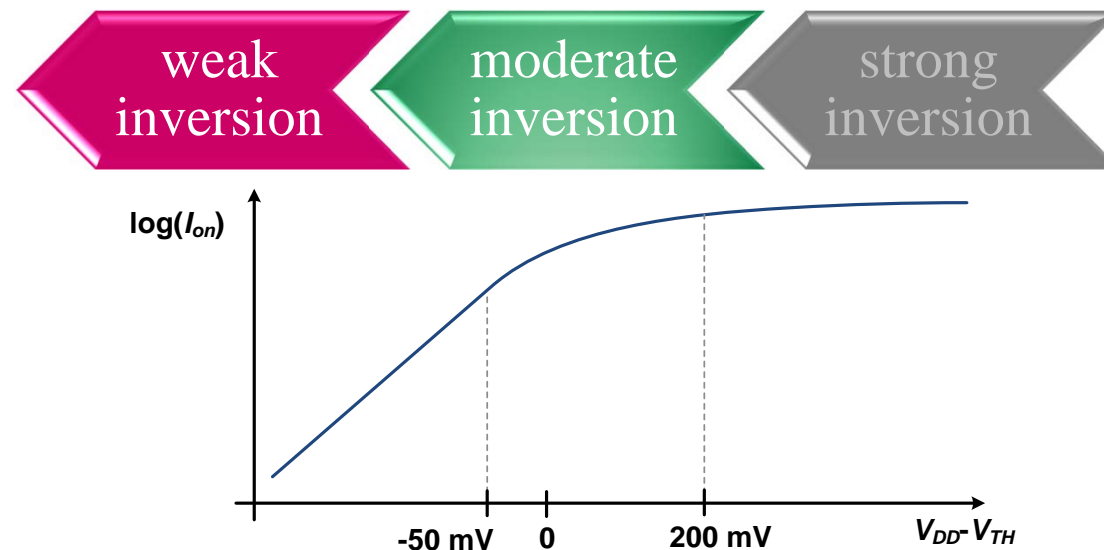


- ◆ How aggressively should we scale V_{DD} ?
 - ◆ energy-performance tradeoff
 - ◆ **NT**: relatively good speed nearly min. energy,
 - ◆ **ST**: low speed, min. energy



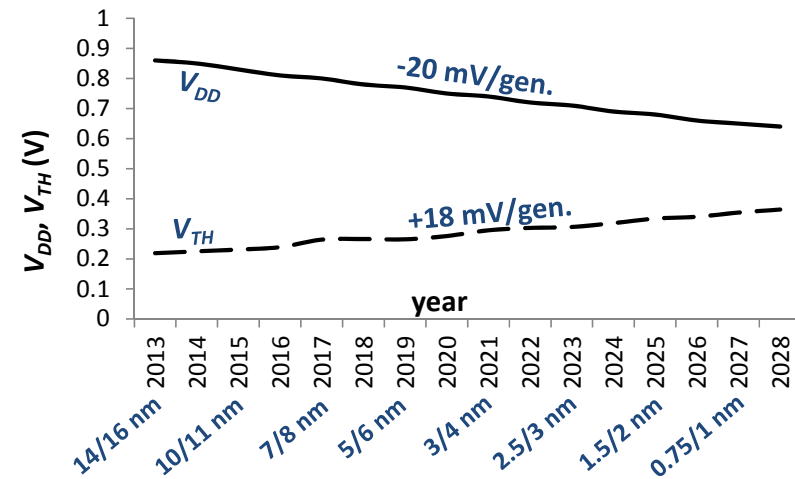
◆ Transistor operation for IoT systems

- ◆ V_{DD} **close to** or **lower than** the transistor threshold voltage
- ◆ operation in **moderate** or **weak** inversion
 - ◆ region defined by gate overdrive $V_{DD}-V_{TH}$
 - ◆ **NT**: $V_{DD} \in [V_{TH}-50\text{mV}, V_{TH}+200\text{mV}] \Rightarrow V_{DD} \sim \mathbf{400-600\text{ mV}}$
 - ◆ **ST**: $V_{DD} < \mathbf{400\text{ mV}}$



◆ ITRS: V_{DD} , V_{TH} ~ constant

- ◆ voltage range
will not change much



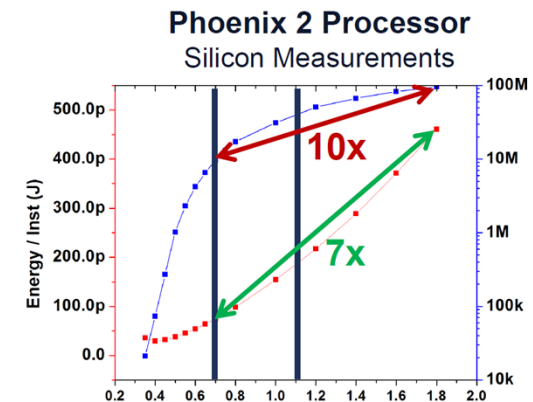
◆ MEP ~ V_{TH}

- ◆ energy ~ minimum (flat minimum)

[CGH11] G. Chen, et Al., “A 1 Cubic Millimeter Energy-Autonomous Wireless Intraocular Pressure Monitor,” ISSCC 2011

◆ choice of region

- ◆ NT: nearly minimum energy, can have high performance via parallelism (power limited, not area limited)
- ◆ ST: minimum power, very lose performance

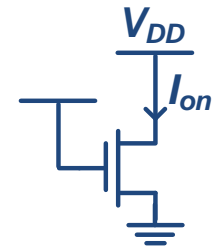
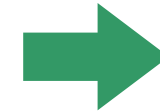
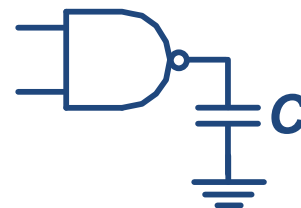


Performance @ ULV: Transistor On-Current

◆ Gate delay: $C \cdot V_{DD} / 2I_{on}$

◆ I_{on} defines performance

gate delay



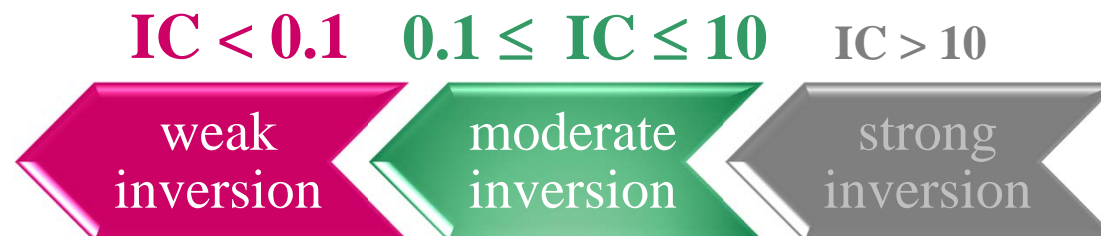
◆ I_{ON} EKV model (transregional) [EV06]

◆ Inversion Coefficient vs gate overdrive

$$I_0 = 2 \cdot n \cdot \mu \cdot C_{OX} \frac{W}{L} v_t^2$$

$$IC = \frac{I_{on}}{I_0} = [\ln(e^v + 1)]^2$$

$v = \frac{V_{DD} - V_{TH}}{2 \cdot n \cdot v_t}$

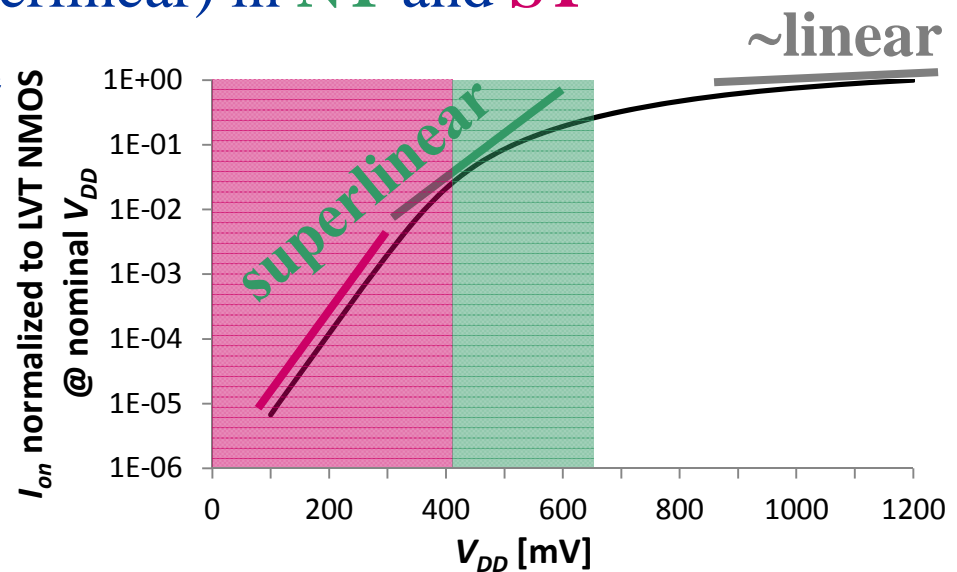


[EV06] C. Enz, E. Vittoz, *Charge-Based MOS Transistor Modeling (...)*, Wiley, 2006

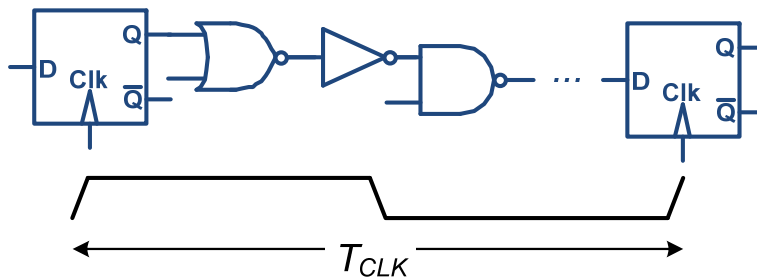
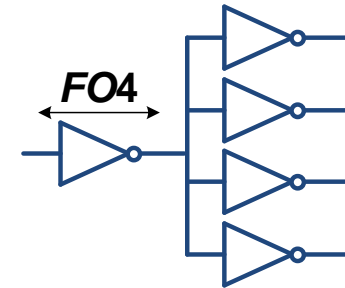
region	V_{DD}	on current
weak inversion	sub threshold	$I_{on} \approx I_0 \cdot e^{\frac{V_{DD}-V_{TH}}{n \cdot v_t}}$
moderate inversion	near threshold	$I_{on} \approx 0.54 \cdot I_0 \cdot (v + 0.88)^2$
strong inversion	above threshold	$I_{on} \approx I_0 \cdot [v]^\alpha \quad (\alpha \sim 1)$

◆ I_{ON} vs V_{DD} : steep (superlinear) in NT and ST

- ◆ performance sensitive to both V_{DD} and V_{TH}
- ◆ choice of V_{TH} really critical
- ◆ sensitivity to V_{DD} , V_{TH} variations...

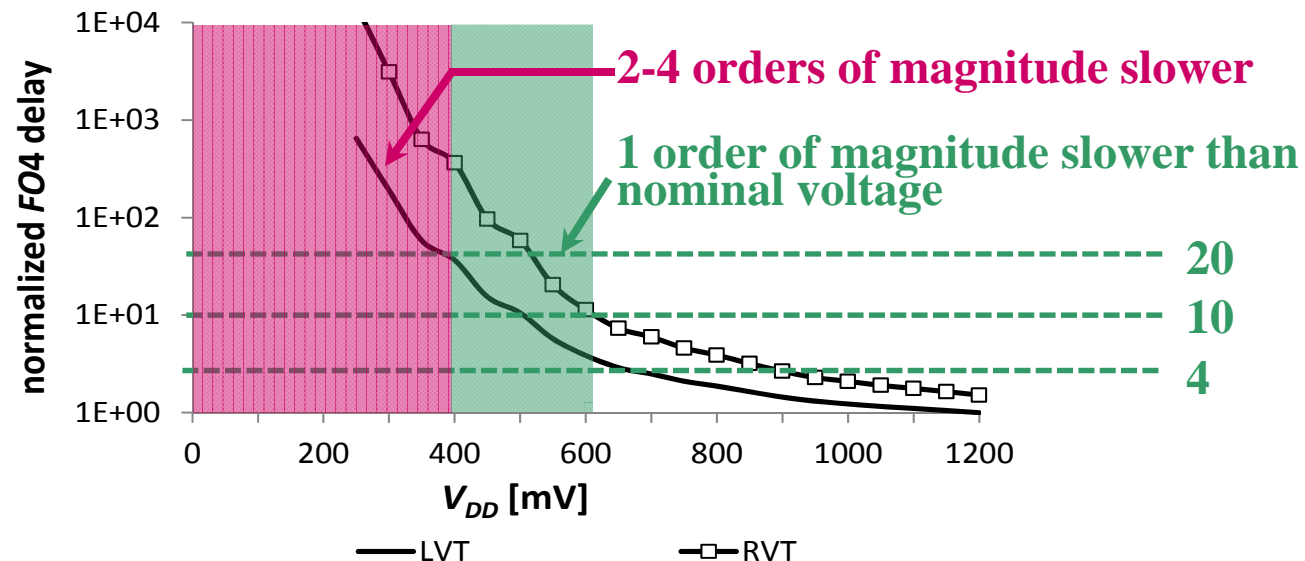


- ◆ Performance: fan-out-4 delay ($FO4$)
 - ◆ speed of technology and (μ)architecture



effective logic depth

$$T_{CK} = LD_{eff} \cdot FO4$$



-
- ◆ Leveraging high sensitivity of I_{on} to V_{DD} @ NT
 - ◆ V_{DD} powerful knob to dynamically improve performance
 - ◆ performance improvement due to $\Delta V=100\text{-mV}$ boosting

V_{DD}	$FO4$ improvement
200 mV	7.5X
400 mV	3.6X
600 mV	1.6X
800 mV	1.2X
1 V	1.1X

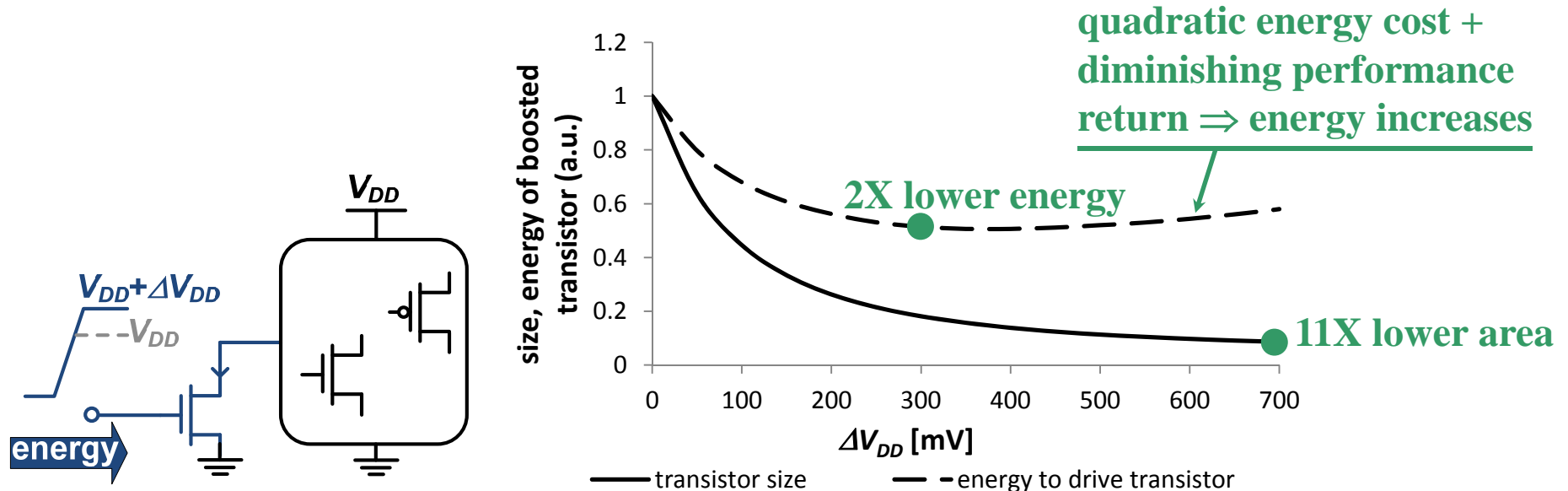
ST: 8X improvement/100 mV

NT: 2-4X improvement/100 mV

- ◆ **ST**: more effective, pretty useless (low performance anyway)
- ◆ **NT**: effective and low energy cost (ΔV is small fraction of V_{DD})
- ◆ **ST** and **NT**: can effectively compensate performance variations

◆ Selective voltage boosting largely improves area and energy efficiency at **NT** and **ST**

- ◆ sizing has a linear impact on transistor strength
- ◆ boosting: superlinear \Rightarrow smaller transistor at iso-strength
- ◆ example at **NT** ($V_{DD}=500$ mV)



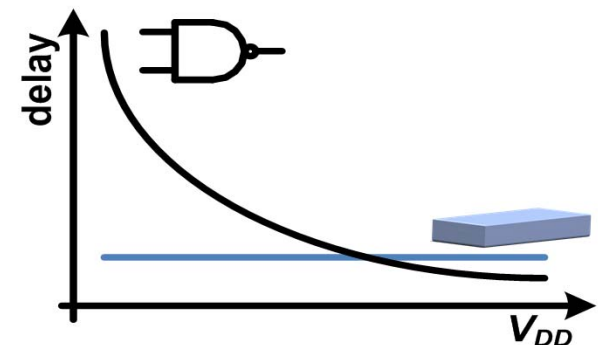
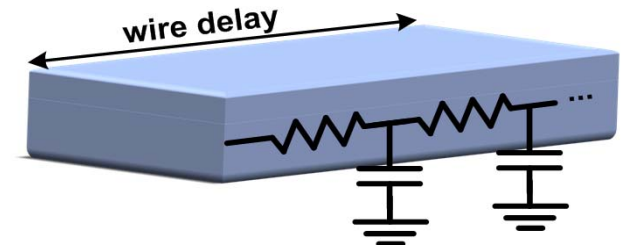
Design Issues and Solutions at Ultra-Low Voltages: Performance

Performance Degradation

- ◆ Performance at **NT/ST** worse than nominal voltage
 - ◆ can be acceptable in practical situations
 - ◆ tasks of IoT nodes are often relatively simple
 - ◆ example of typical throughput: few **hundreds of Mops/s** (e.g., video processing) down to **kops/s** (e.g., temperature monitoring)

- ◆ Wire delay at **NT/ST**

- ◆ gate delay increases at ULV ($>10X$)
- ◆ wire delay is constant
- ➔ ◆ gate delay much less critical than nominal V_{DD}
 - ◆ design as in the “good old days”



◆ If higher performance is sometimes needed...

- ◆ wide voltage scaling
(e.g., from 400 mV to 1.2 V)



- ◆ large performance improvement (10X)
- ◆ energy/op increases quadratically (9X)
- ◆ tolerable if occasional

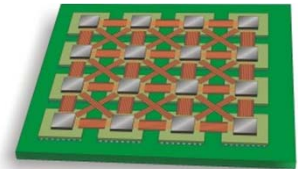
$$E_{dyn} \propto C \cdot V_{DD}^2$$

- ◆ optimized for NT
- ⇒ **energy/performance tradeoff**
at 1.2 V is degraded

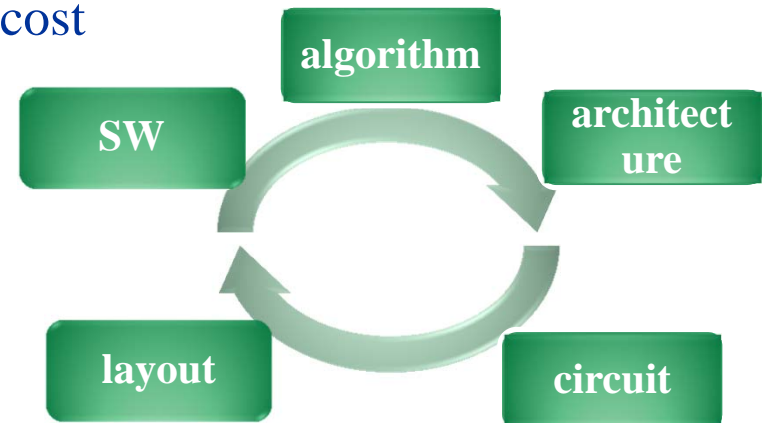
Design Characteristics	Synthesis Corner	
	0.5V, 80MHz	1.05V, 650MHz
Performance Range (0.5V-1.05V)	1X-8X	0.6X-6.5X
Leakage Power	1X	0.8X
Total Device Width	1X	0.78X

[J12] S. Jain, et Al., IEEE ISSCC Dig. Tech. Papers, pp. 66–67, Feb. 2012

Design Corner Evaluations



- ♦ trading off area for performance: parallelism
 - ♦ **intra-chip communication** limits perf./energy gains
 - ♦ **specificity of task** can be leveraged for better balance of computation/communication cost
- ♦ **across-level design** is required to manage these tradeoffs

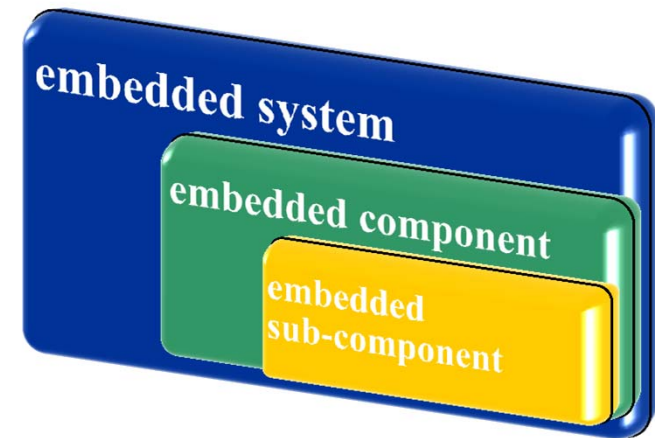


NT

~~ST~~



- ◆ trading off area for performance: specialized HW
 - ◆ example: FFT, Java processor, AES, MPEG decoder...
 - ◆ specialized HW has better performance/energy tradeoff than general-purpose
 - ◆ larger benefit for **recurrent and specific tasks**



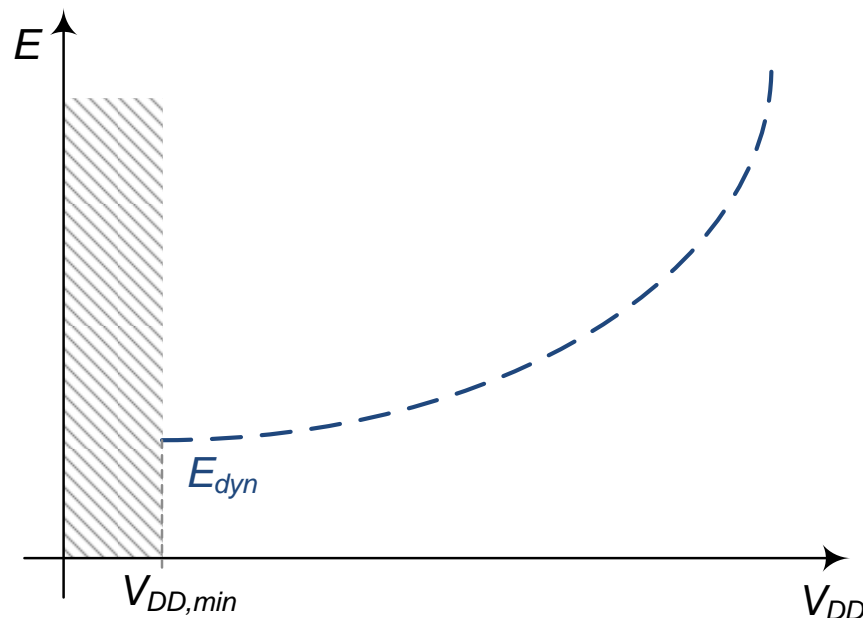
Design Issues and Solutions at Ultra-Low Voltages: Leakage

Energy vs V_{DD}

- ◆ If dynamic energy per operation dominates:

$$E_{dyn} = \alpha_{SW} \cdot C \cdot V_{DD}^2$$

- ◆ reduce V_{DD} as much as possible
 - ◆ energy reduction limited by $V_{DD,min}$ (defined by robustness issues, very different for logic and memory)



V_{DD} (mV)	V_{DD}^2 energy saving	including $C_g(V_{DD})$
200 mV	36X	54X
400 mV	9X	11.6X
600 mV	4X	4.4X
800 mV	2.2X	2.4X
1 V	1.4X	1.4X
1.2 V	1X	1X

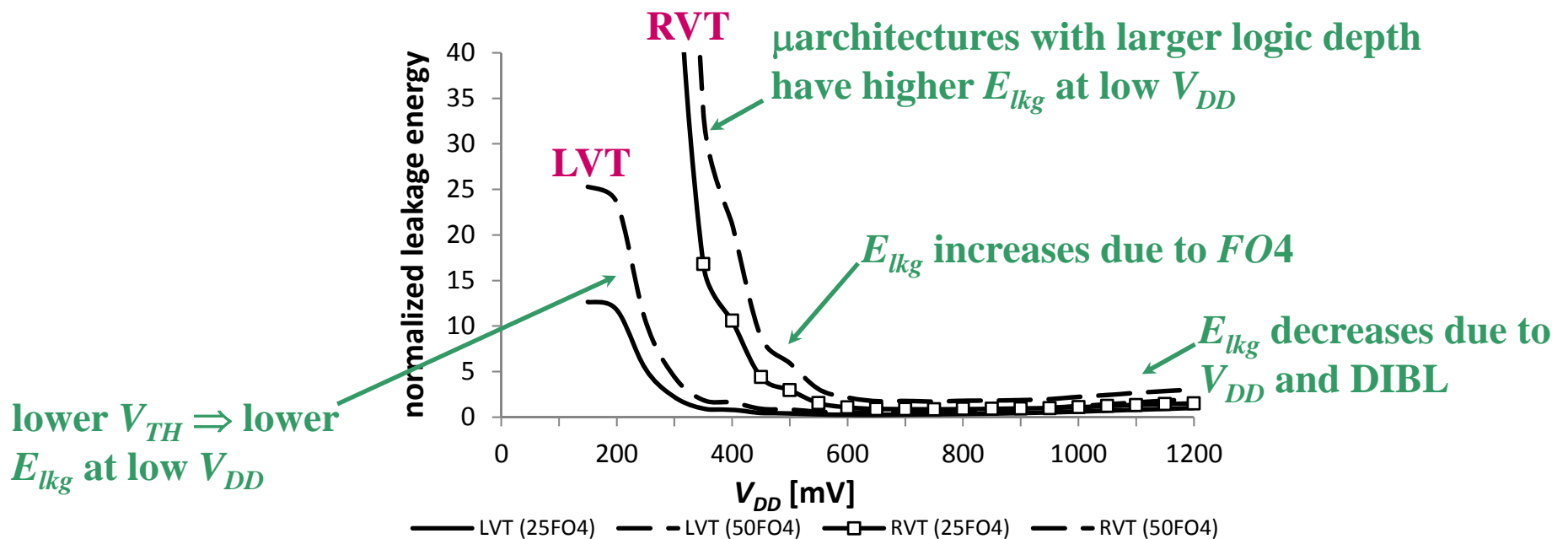
- ◆ If leakage energy per operation dominates:



$$E_{lk g} = V_{D D} \cdot I_{o f f} \cdot F O 4 \cdot L D_{e f f} \cdot C P O$$

architecture
ckt
technology
cycles/op

- ◆ at **NT** and **ST**, increases significantly (*FO4* increase)
 - ◆ example in 28nm:



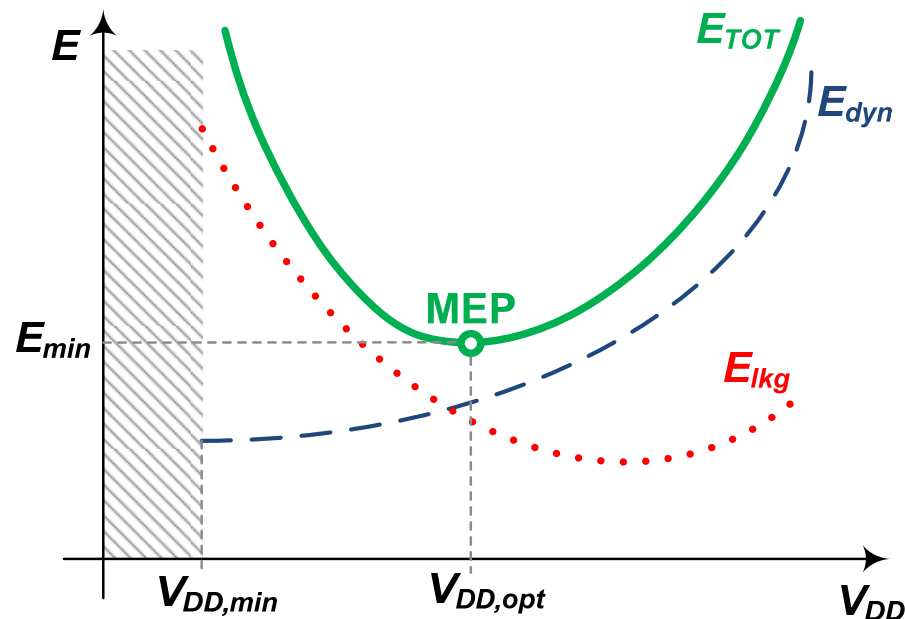
Minimum Energy Point

◆ Combining dynamic and leakage energy



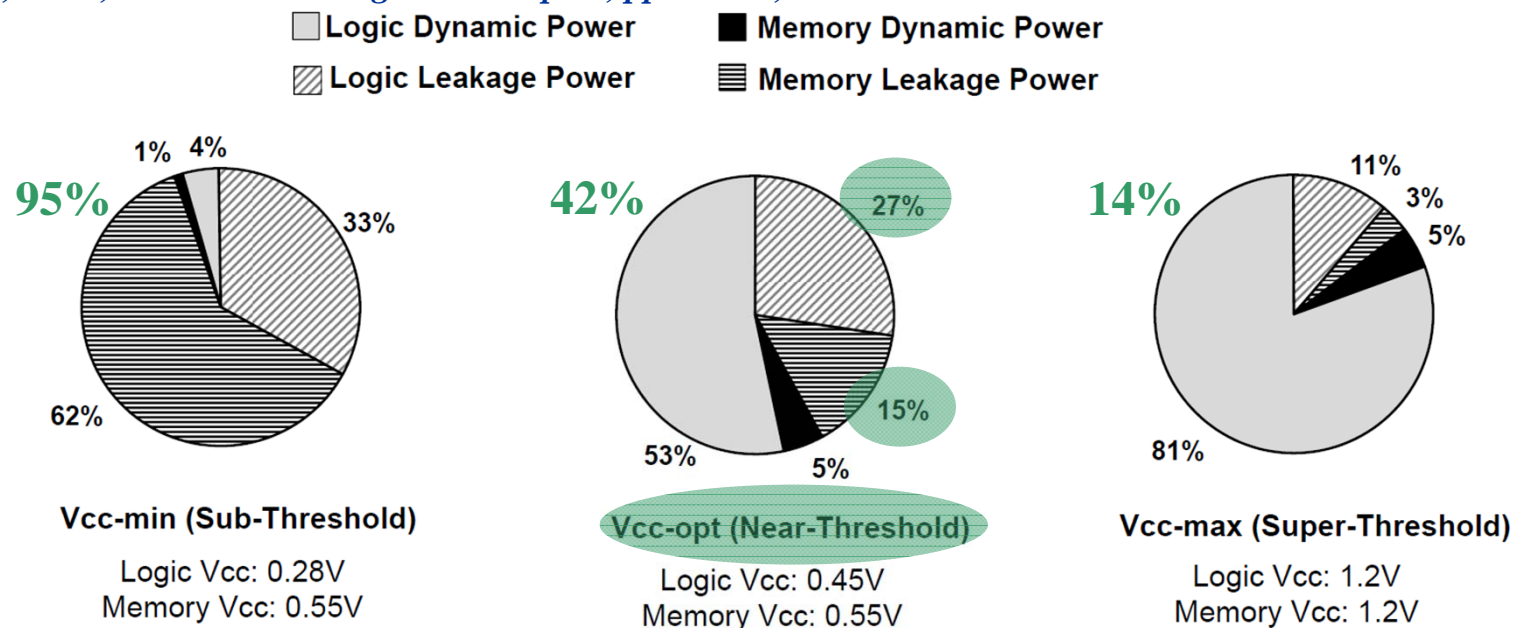
◆ minimum energy point (MEP)

- ◆ relatively **flat** (V_{DD} mainly set by performance target)
- ◆ can lie in either **NT** or **ST**
- ◆ **time varying**: depends on temperature, data set...



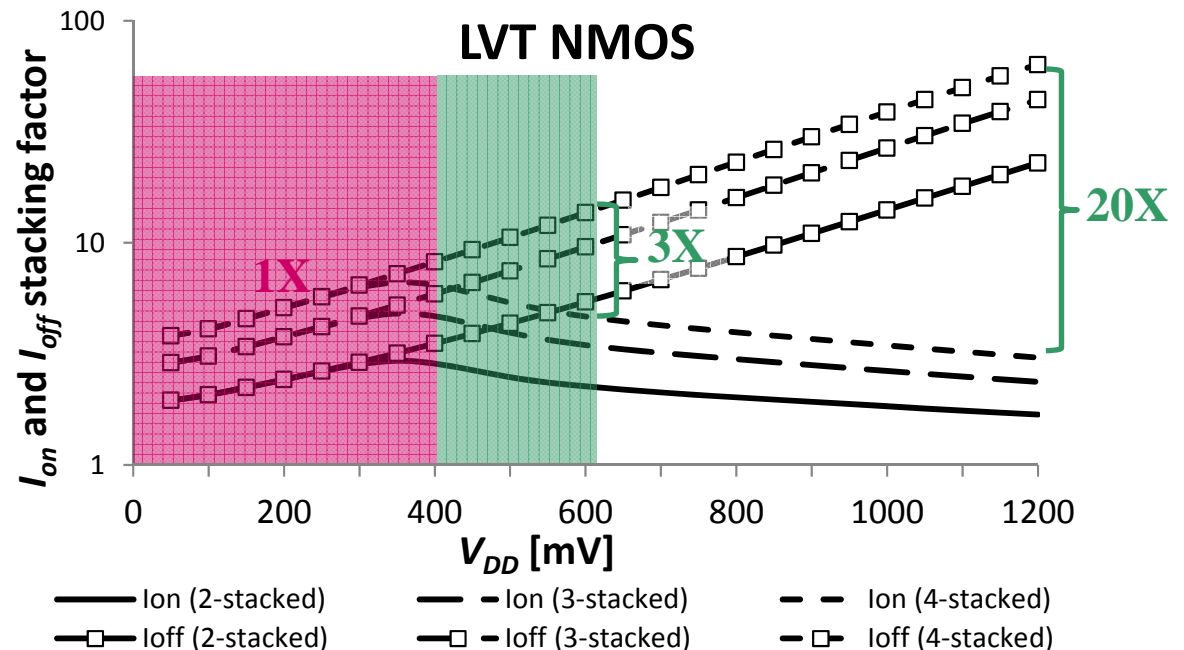
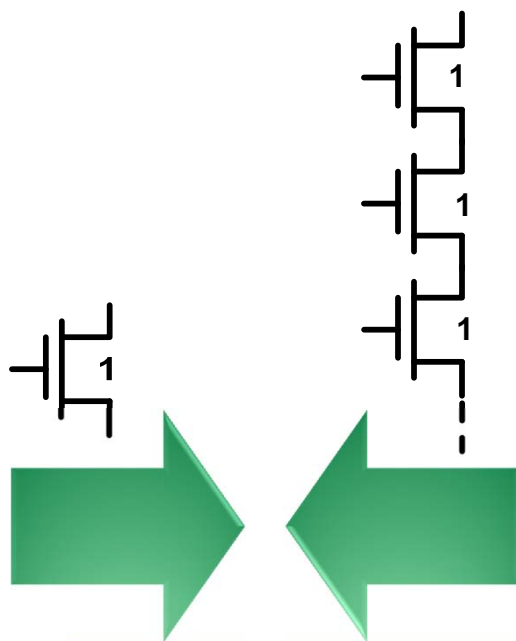
- ◆ Leakage energy takes up increasingly larger fraction of total energy at lower V_{DD}
 - ◆ at low V_{DD} , leakage energy increases exponentially, dynamic energy decreases quadratically
 - ◆ ex.: processor with L1 cache ($V_{DDcache,min}=0.55$ V)

[J12] S. Jain, et Al., *IEEE ISSCC Dig. Tech. Papers*, pp. 66–67, Feb. 2012

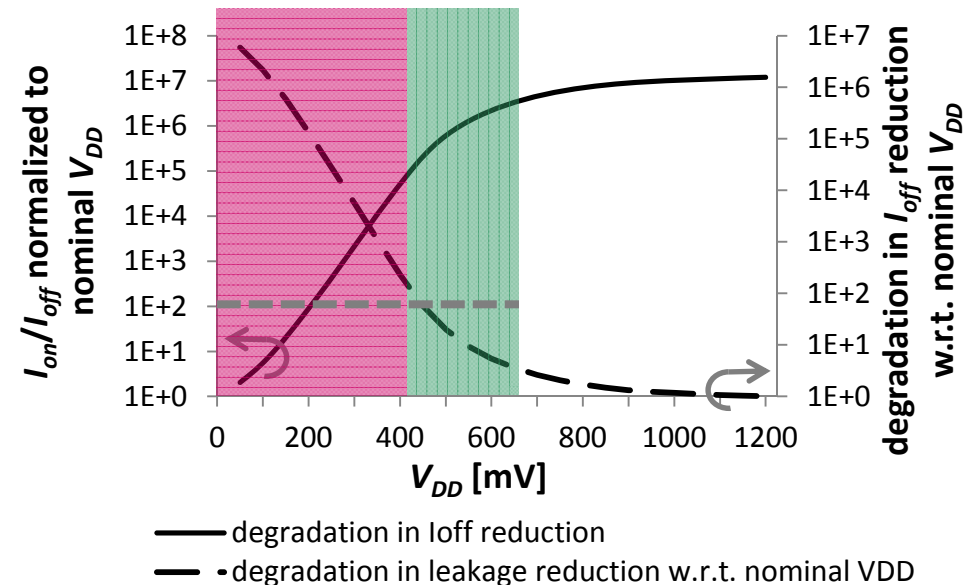
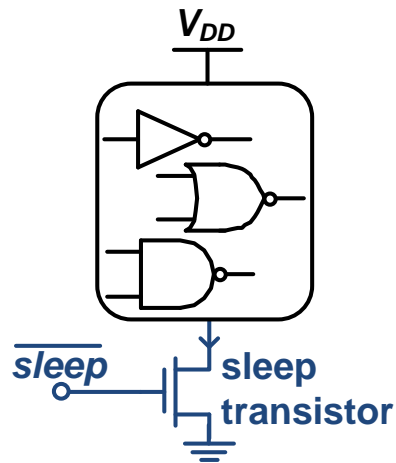


Traditional Techniques for Low Leakage

- ◆ Leakage is truly critical (process not enough)
 - ◆ large, limits energy reduction
- ◆ Several traditional circuit techniques do not work...
 - ◆ **transistor stacking** is ineffective



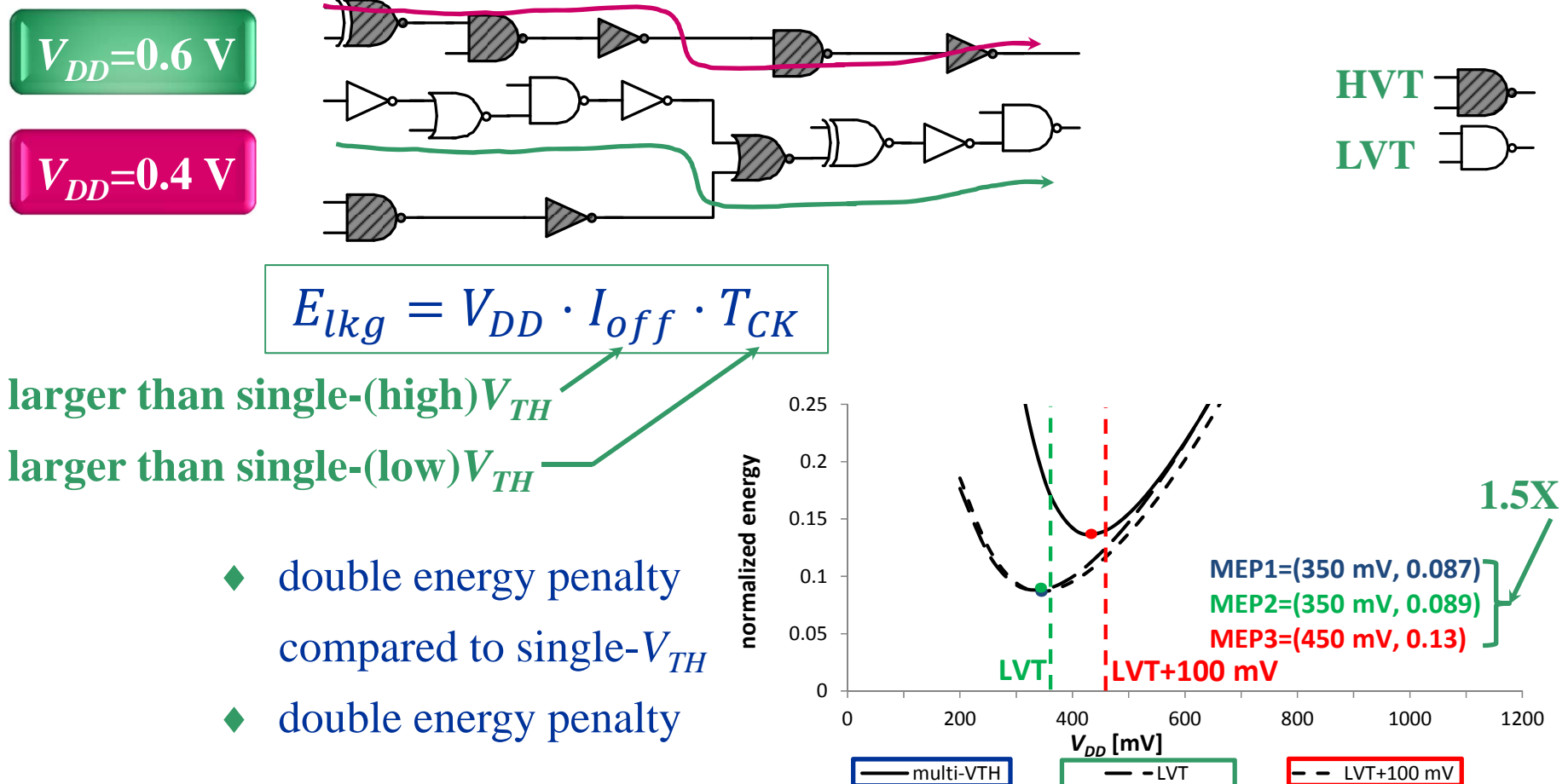
- ◆ **power gating** is much less effective (I_{on}/I_{off} degradation)



- ◆ typical leakage reduction: 10-100X
 - ◆ **NT**: small leakage reduction, **ST**: no leakage reduction at all
 - ◆ solution: boost gate voltage of sleep transistor (increases I_{on}/I_{off})
- selective voltage boosting

◆ multi- V_{TH} actually degrades energy efficiency

- ◆ delay sensitive to $V_{TH} \Rightarrow$ critical path changes at scaled V_{DD}

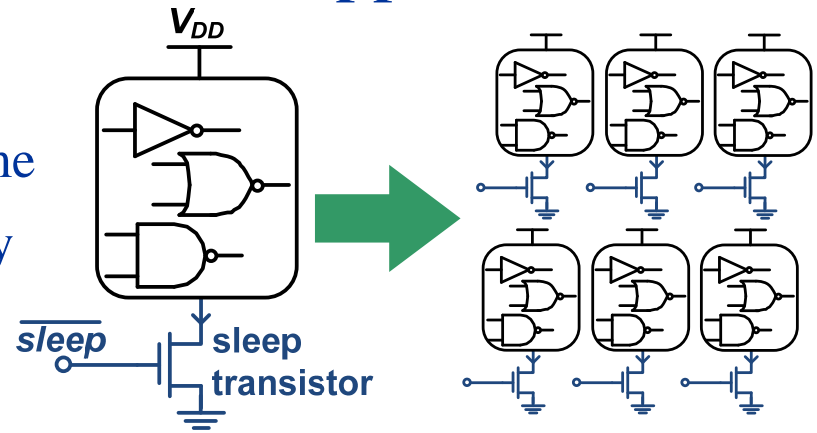


Counteracting Leakage at ULV

◆ Leakage reduction at ULV: alternative approaches

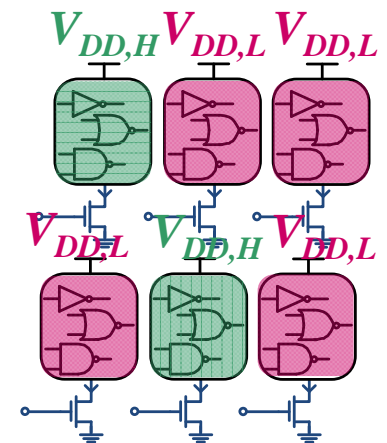
◆ fine-grain power gating

- ◆ disable unused blocks at runtime
- ◆ small \Rightarrow quickly and frequently
- ◆ **overhead**: multiple sleep transistors, isolation, control
- ◆ lower control overhead via ckt/architectural support for SW



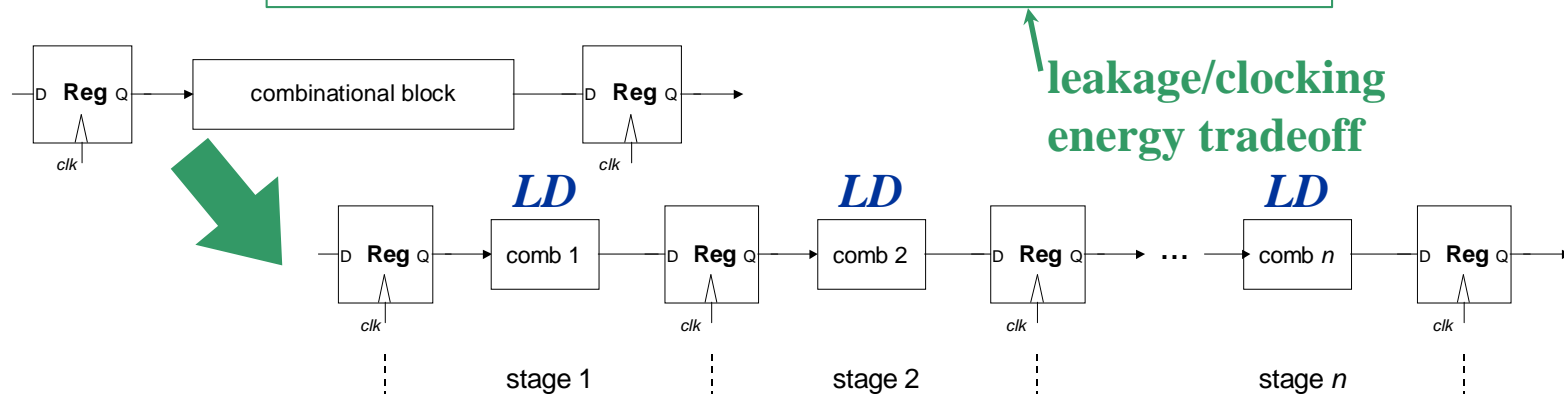
◆ fine-grain voltage domains

- ◆ E_{lkg} reduced at lower V_{DD} (e.g., 2X/100 mV)
- ◆ selectively reduce V_{DD} wherever possible (slower)
- ◆ similar considerations as power gating

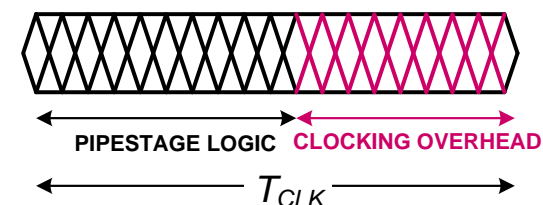


◆ microarchitecture-circuit co-design: pipelining

$$E_{lkg} = V_{DD} \cdot I_{off} \cdot FO4 \cdot \mathbf{LD}_{eff} \cdot CPO$$



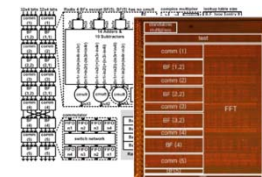
- ◆ use **deep pipelines** + refined circuit techniques/methodologies to deal with clocking overhead



- ◆ example: 17FO4/stage in FFT engine

(30MHz @ 0.27V, 4X less energy than state of the art)

[AJC11] M. Seok, et Al. "A 0.27V, 30MHz, 17.7nJ/transform 1024-pt complex FFT core with super-pipelining," ISSCC 2011

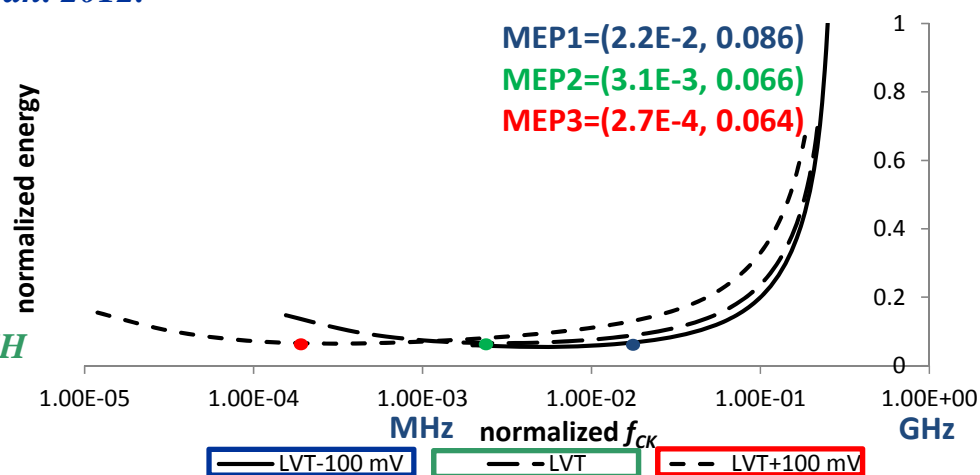
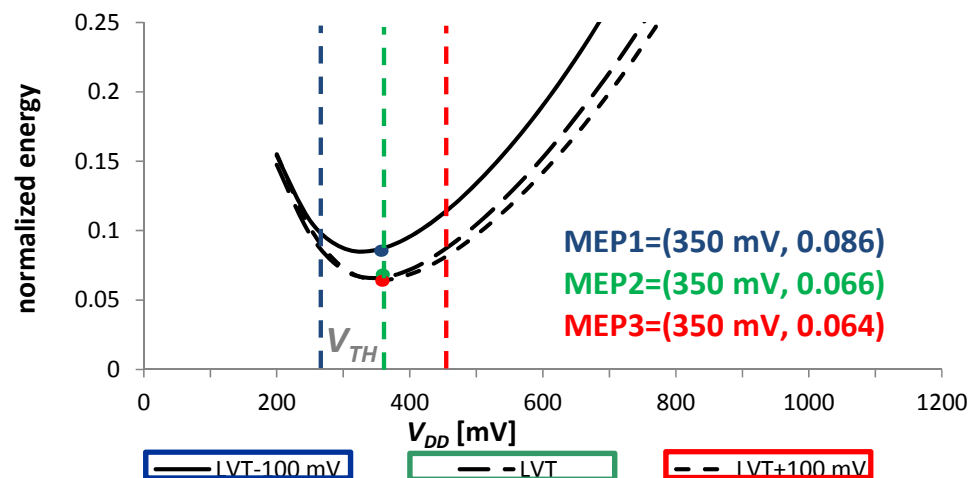


- ◆ V_{TH} selection
 - ◆ energy-optimal $V_{DD,opt}$ is independent of V_{TH}
 - ◆ choose V_{TH} according to performance target

[A12] M. Alioto, “Ultra-Low Power VLSI Circuit Design Demystified and Explained: A Tutorial,” *IEEE TCAS-I*, Jan. 2012.

- ◆ performance: changes by 10X per V_{TH} flavor
- ◆ strong process- μ arch. interaction through V_{TH}

- ◆ body biasing
 - ◆ makes sense in FDSOI (V_{TH} sensitivity to V_{BB} large enough)



Design Issues and Solutions at Ultra-Low Voltages: Variability and Resiliency

Variations: Why do They Matter?

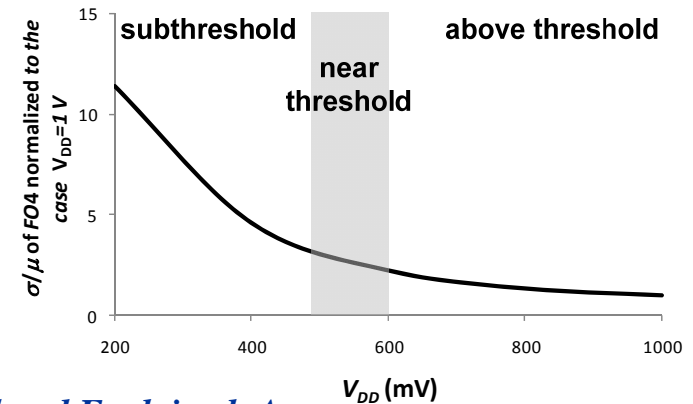
◆ Resiliency degraded at ULV

◆ process/voltage/temperature

◆ larger than at nominal V_{DD}

◆ ageing, soft errors...

[A12] M. Alioto, "Ultra-Low Power VLSI Circuit Design Demystified and Explained: A Tutorial," *IEEE TCAS-I*, Jan. 2012.



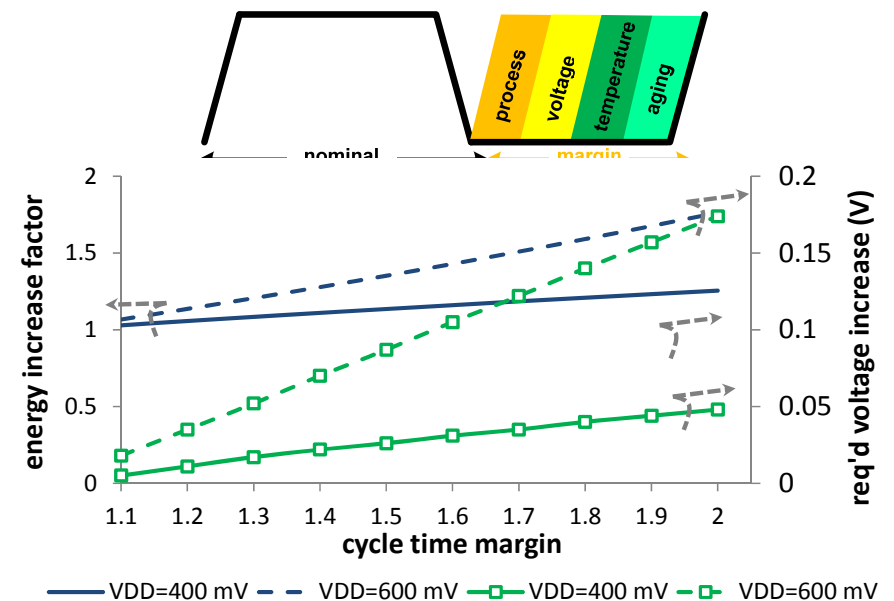
◆ design margining

◆ cycle margin

(20-30% @ full V_{DD})

◆ degrades performance
AND energy efficiency

◆ large energy penalty



Process Variations

◆ Variability of delay (mainly due to I_{on})

- ◆ random variations are dominant (area-mismatch tradeoff)
- ◆ two negative effects arise at NT [GIS11]

Random Dopant
Fluctuation, Line Edge
Roughness...



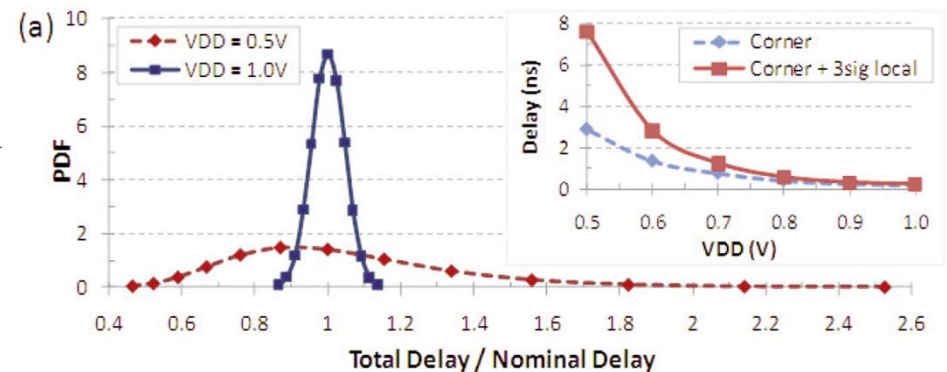
Larger variability σ/μ

- ◆ due to larger sensitivity of I_{on} to V_{TH}

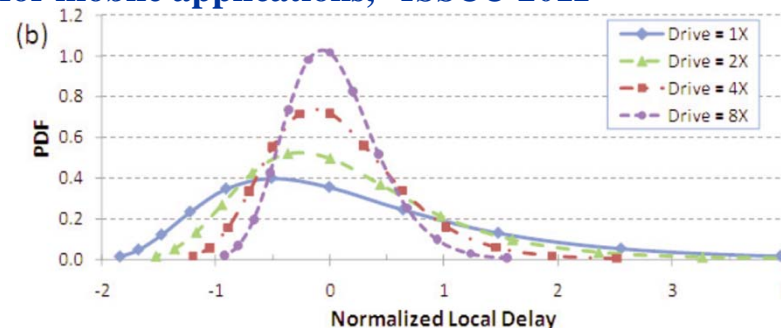


PDF heavily non-Gaussian

- ◆ in subthreshold tends to lognormal
- ◆ right skewed \Rightarrow average $>$ nominal
- ◆ larger no. of σ s for given yield



[GIS11] G. Gammie, et Al., "A 28nm 0.6V low-power DSP for mobile applications," ISSCC 2011





◆ Semi-quantitative analysis of I_{on} variations

Larger variability σ/μ

Above threshold

$$I_{on} \propto \left(1 - \frac{\Delta V_{TH}}{V_{DD} - V_{TH}}\right)$$

$$\Rightarrow \frac{\sigma_{I_{on}}}{\mu_{I_{on}}} = \frac{\sigma_{V_{TH}}}{V_{DD} - V_{TH}}$$

ex. $V_{DD}=0.9$ V, $V_{TH}=0.36$ V, $\sigma_{V_{TH}}=35$ mV

\Rightarrow **6.5%**

Subthreshold

$$I_{on} \propto e^{-\frac{\Delta V_{TH}}{n \cdot v_t}}$$

$$\Rightarrow \frac{\sigma_{I_{on}}}{\mu_{I_{on}}} = \sqrt{e^{\left(\frac{\sigma_{V_{TH}}}{n \cdot v_t}\right)^2} - 1}$$

ex. $\sigma_{V_{TH}}=35$ mV, $n=1.35$

\Rightarrow **131% (20X)**

◆ at NT, σ/μ is intermediate (**$\sim 4-5X$**)

Larger no. of σ

◆ no. of std deviations (yield)

◆ at NT: somewhat intermediate

◆ ex. @ 3σ for single gate:

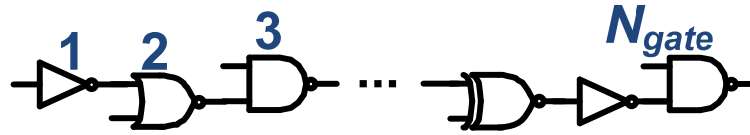
margin = $10\sigma/\mu = 300\%$

YIELD	Gaussian	lognormal
84%	σ	$e \cdot \sigma$
97.7%	2σ	$e^2 \cdot \sigma \approx 7.4\sigma$
99.9%	3σ	$e^3 \cdot \sigma \approx 20.1\sigma$

◆ Variability/leakage tradeoff unavoidable

◆ averaging effect reduces variability by

cascading ◆ cascaded logic gates



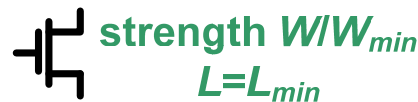
$$\frac{\sigma}{\mu} = \frac{1}{\sqrt{N_{gate}}}$$

stacking ◆ stacked transistors



$$\frac{\sigma}{\mu} = \frac{1}{\sqrt{N_{stacked}}}$$

strength ◆ larger transistors



$$\frac{\sigma}{\mu} = \frac{1}{\sqrt{strength}}$$

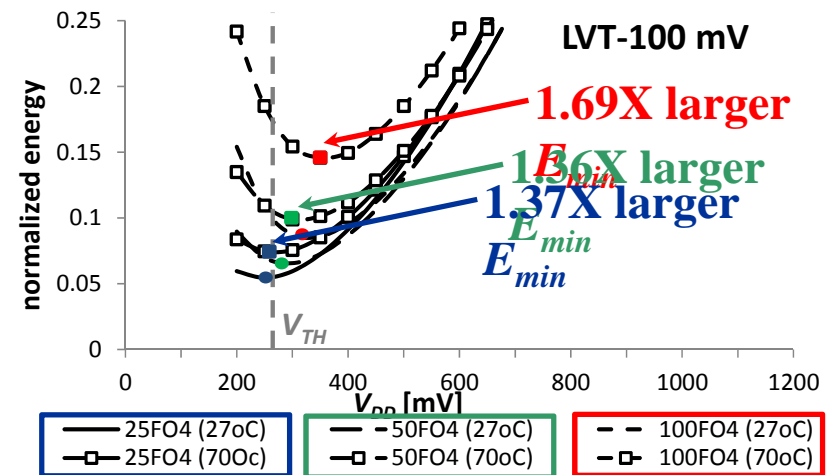
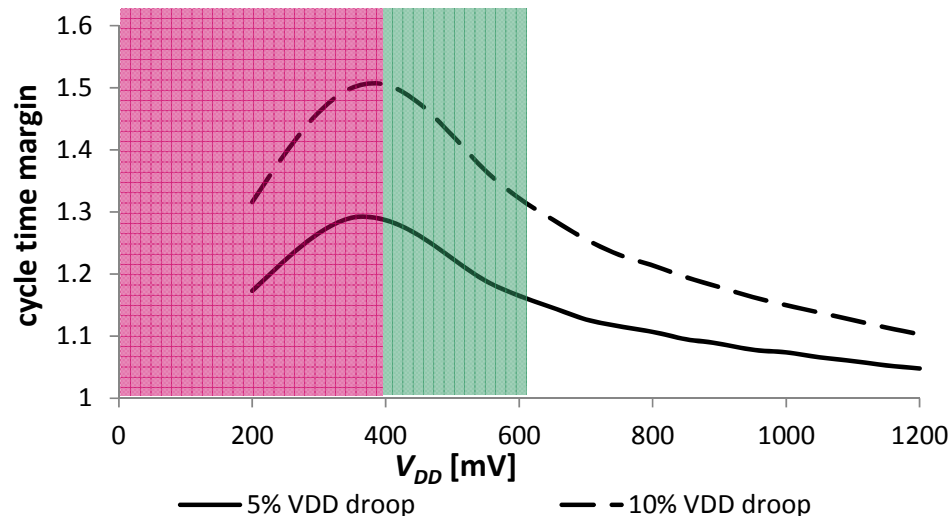
◆ path delay variability from $FO4$ variability (min. sized)

$$n_{\sigma} \frac{\sigma_{pathdelay}}{\mu_{pathdelay}} = n_{\sigma} \sqrt{\left(\frac{\sigma_{FO4,D2D}}{\mu_{FO4,D2D}} \right)^2 + \frac{\left(\frac{\sigma_{FO4,random}}{\mu_{FO4,random}} \right)^2}{N_{gate} \cdot strength \cdot N_{stacked}}}$$

[MWA10] M. Merrett, et Al., “Design Metrics for RTL Level Estimation of Delay Variability Due to Intradie (Random) Variations,” ISCAS 2010

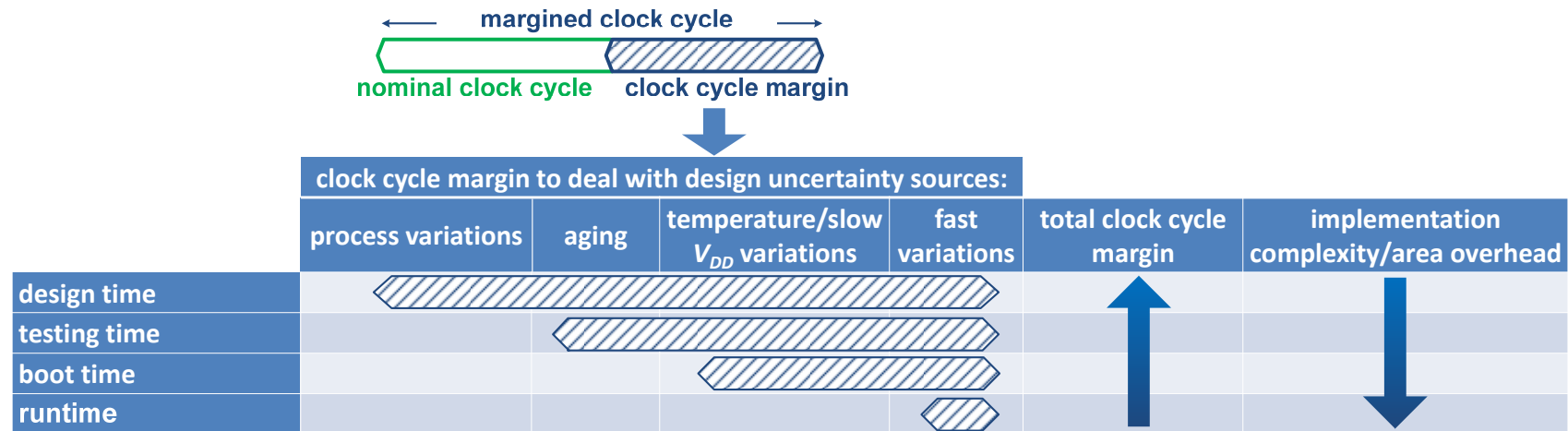
Voltage/Temperature Variations

- ◆ Delay is very sensitive to V_{DD} and temperature
 - ◆ voltage: up to 30-50% margin
 - ◆ temperature: up to 2X margin
 - ◆ NT systems require **adaptive schemes**
 - ◆ sense V_{DD} and T and adjust clock cycle
 - ◆ can compensate **slow variations** (margin needed for fast)



Clock Cycle Margin Reduction/Elimination

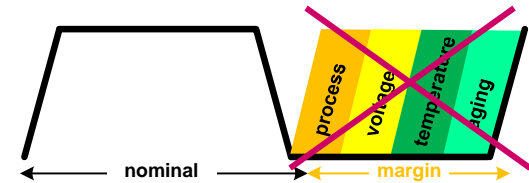
◆ Compensation of variations at different times



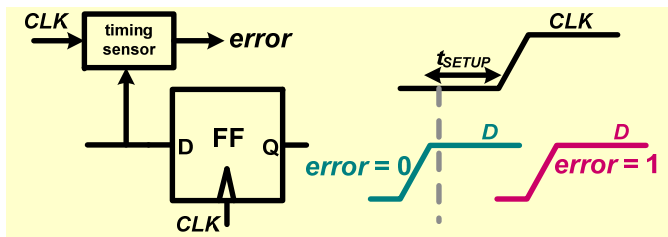
- ◆ tradeoff between energy cost of margining vs energy cost to reduce amount of margin
- ◆ large variations at **NT/ST**: runtime compensation usually required
- ◆ detect timing errors/correct: minimum or no margin at all

Margin Elimination: Timing Error Detection

- ◆ Reduce/eliminate worst-case margin by catching delay faults

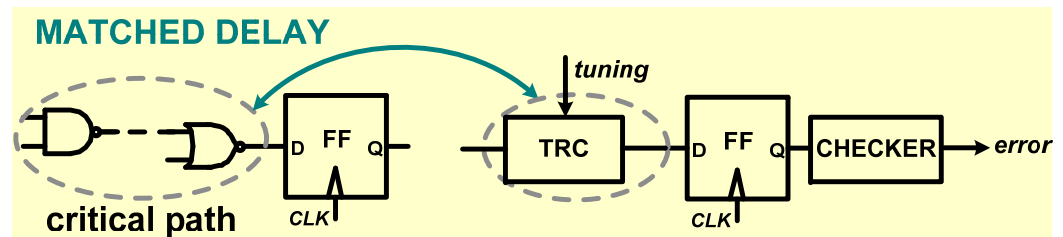


- ◆ correct at run-time, tune to compensate actual variations
- ◆ can speculatively reduce energy (if critical path is infrequent)



In-situ monitoring

- ◆ P, V, T, aging, fast variations
- ◆ no margin
- ◆ invasive, limited tuning



Fault prediction (Tunable Replica Circuit)

- ◆ partially: P, V, T, aging, fast (not soft errors)
- ◆ needs some margin (false positives, mimics only critical path)
- ◆ little invasive, tuning required, low overhead

Margin Elimination: Error Correction

- ◆ Faults can be corrected at various levels
 - ◆ across-level design/optimization/control needed
- faster correction**



less HW resources



lower energy/performance penalty

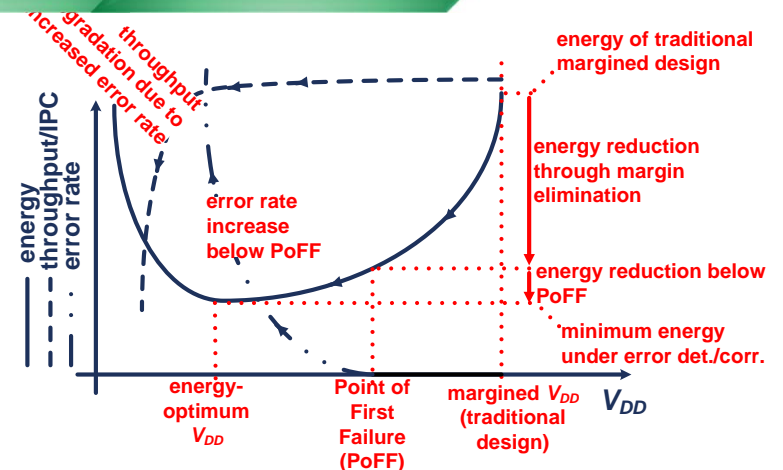


- ◆ energy overhead

$$E = E_{\text{correction}} \cdot \text{error rate} +$$

$$+ f \cdot C \cdot V_{DD}^2$$

- ◆ **testing is painful** (long, tuning)



A Step Forward: Sub-Cycle Detection/Correction

- ◆ Most existing approaches are cycle-based

	Area	Power	Complexity	Recovery Time ^a
Clock Gating	High	High	Impractical	1 cycle
Counterflow	Medium	Medium	Medium	1 + (N – 1) cycles
Micro-Rollback	High	High	High	N cycles
Multiple Issue	Low	Low	Low	2N + 2 cycles

[CKM11] J. Crop, et Al., “Error Detection and Recovery Techniques for Variation-Aware CMOS Computing: A Comprehensive Review” *JLPEA 2011*

- ◆ correction **interferes with microarchitecture** (design effort)
 - ◆ errors affect timing at boundary: **difficult SoC integration**
 - ◆ large **energy penalty** in high error rate regime (future)
- ◆ The future of detection/correction
 - ◆ **sub-cycle** detection/correction with low overhead
 - ◆ errors detected/corrected in the same cycle
 - ◆ or, at least, errors do not have to propagate to the boundary
 - ◆ so that **errors are confined** and determine **low energy penalty**

Approximate Computing: Negative Margining

- ◆ Some apps do not need to have perfect computation
 - ◆ approximate computing (deterministic, voltage overscaling)
 - ◆ ex.: multimedia, sensor fusion
 - ◆ errors not corrected on the fly
 - ◆ **avg error rate** kept within bound (slow correction loop)
 - ◆ ex.: our first SRAM with Dynamically Adjustable Error-Quality

[FKB14] F. Frustaci, et Al., “A 32kb SRAM for Error-Free and Error-Tolerant Applications with Dynamic Energy-Quality Management in 28nm CMOS,” ISSCC 2014



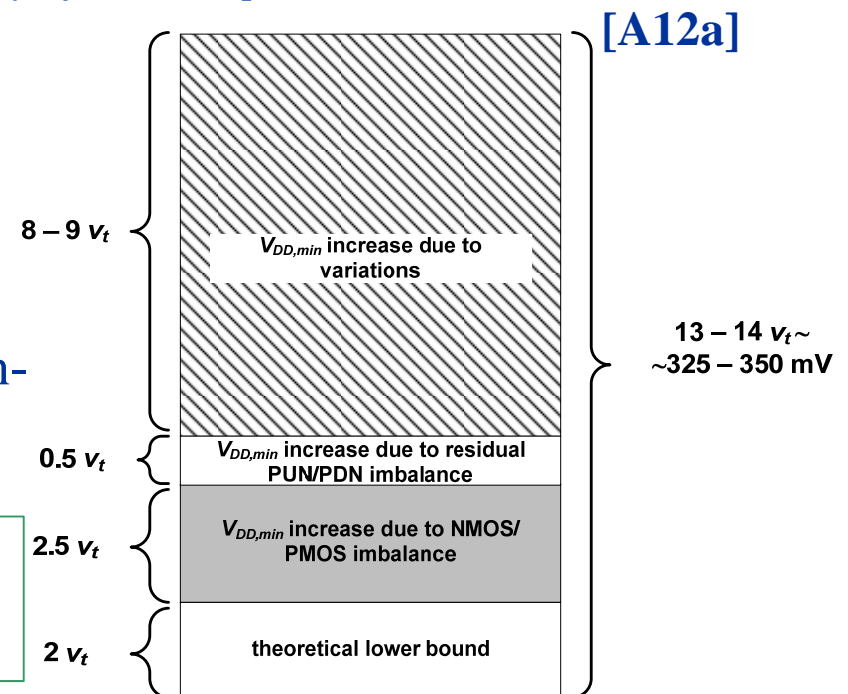
Functional Failures and $V_{DD,min}$

- ◆ Functional failures occur at very low V_{DD}
 - ◆ flip-flops/latches prone to such failures (highest $V_{DD,min}$)
 - ◆ due to multiple connected outputs (current contention due to low I_{on}/I_{off})

[A12a] M. Alioto, “Ultra-Low Power VLSI Circuit Design Demystified and Explained: A Tutorial,” *IEEE TCAS-I*, Jan. 2012.

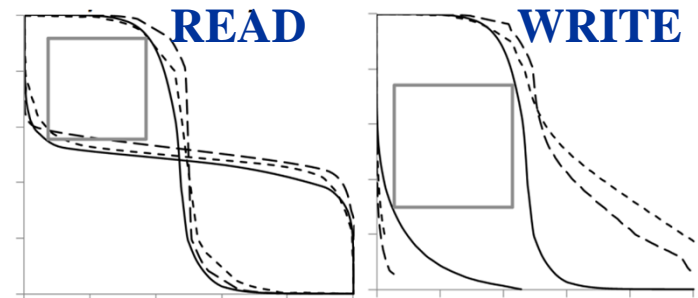
- ◆ large worst-case variations due to high number of FFs (millions)
- ◆ $V_{DD,min}$ dominated by variation-induced p/n imbalance [A12a]

$$V_{DD,min} = n \cdot v_t \cdot \left[1 + \ln\left(\frac{2}{n}\right) + \ln(pn) \right]$$



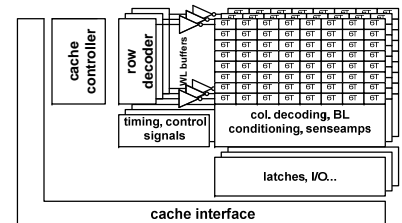
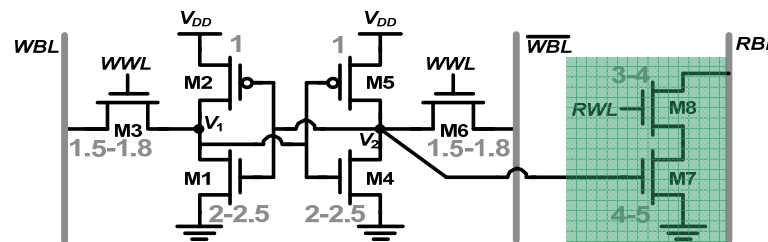
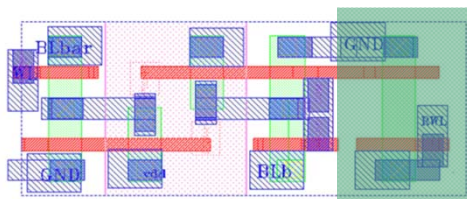
- ◆ SRAM more vulnerable than logic

- ◆ read/write/hold margins set by strength ratio
- ◆ no averaging across multiple cells, as opposed to logic



- ◆ reducing $V_{DD,min}$ of SRAMs at different levels

- ◆ **within** the cell: V_{TH} adjustment, lithography-friendly layout, circuit (sizing, more robust topologies)
- ◆ **outside** the cell: array architecture, assist techniques

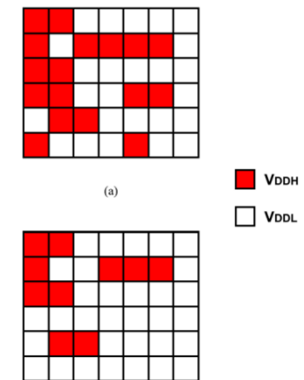


Fine-Grain Adaptation

◆ Multi- V_{DD} with small area/energy overhead

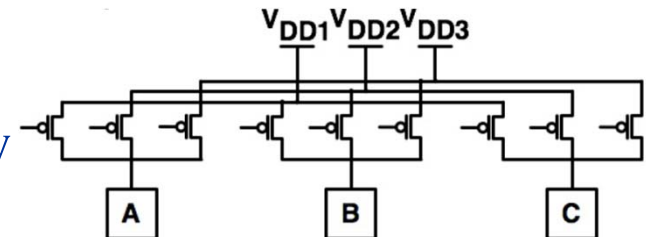
- ◆ avoid level shifters altogether [MYN11]
 - ◆ small voltage domains dynamically assigned
 - ◆ no level shifters (small voltage difference)

[MYN11] A. Muramatsu, et Al. "12% Power Reduction by Within-Functional-Block Fine-Grained Adaptive Dual Supply Voltage Control (...)," ESSCIRC 2011



◆ Panoptic Dynamic Voltage Scaling [PDC09]

- ◆ spatial and temporal fine granularity
- ◆ sleep transistors (re)used to dynamically select V_{DD} (workload)
- ◆ 34% (44%) energy saving over multi- V_{DD} (single V_{DD})



[PDC09] M. Putic, et Al., "Panoptic DVS: A Fine-Grained Dynamic Voltage Scaling Framework for Energy Scalable CMOS Design," ICCD 2009

◆ Selective boosting, state-retentive sleep [TRA14]

- ◆ Graphics Execution Core
- ◆ V_{DD} of register file/ROM **boosted** by 270 mV to improve $V_{DD,min}$
- ◆ **adaptive clocking** reacts to first V_{DD} droop: senses and divides f_{CLK} for a fixed time to recover (margin reduction)
- ◆ 4-20X register file **leakage reduction** in sleep mode through voltage reduction down to Data Retention Voltage of bitcells

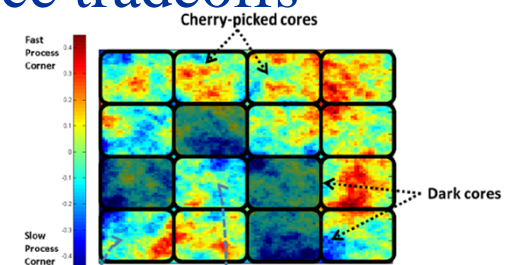
[TRA14] C. Tokunaga, et Al. "A Graphics Execution Core in 22nm CMOS Featuring Adaptive Clocking, Selective Boosting and State-Retentive Sleep," ISSCC 2014

◆ Exploiting variations via **cherry picking** [RTG13]

- ◆ different cores: different energy-performance tradeoffs

- ◆ redundant cores, choose for max performance
- ◆ 22% better performance at 33% dark silicon

[RTG13] B. Raghunathan, et Al., "Cherry-Picking: Exploiting Process Variations in Dark-Silicon Homogeneous Chip Multi-Processors," DATE 2013

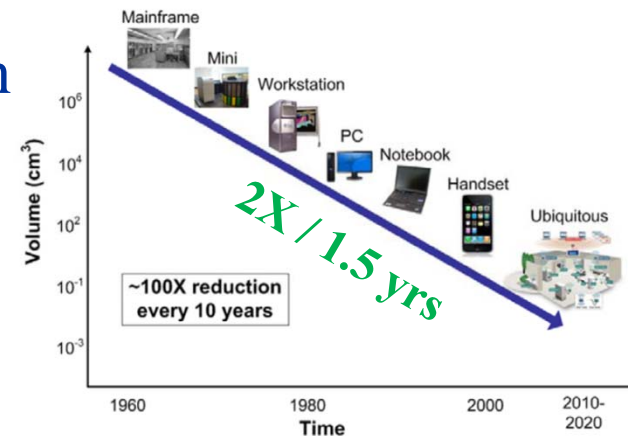


Conclusions

IoT Naturally Follows Historical Trends...

◆ Size is a technology driver for the IoT

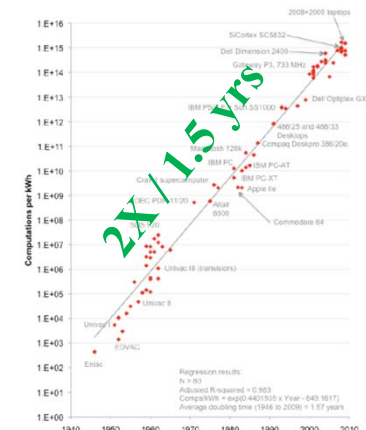
- ◆ **Bell's law:** 10-100X size reduction every 10 years
 - ◆ IoT should happen in this decade



by courtesy of D. Blaauw

◆ **Energy** is the bottleneck for size

- ◆ **Koomey's law** [KBS10]: $2X / 1.6$ years
 - ◆ 75X in 10 years ($\sim 4X$ from technology scaling)
 - ◆ rest of it must come from ckt/architecture/system
 - ◆ quicker development, more aggressive reduction: more innovation



[KBS10] J. Koomey, et Al., “Implications of Historical Trends in the Electrical Efficiency of Computing” IEEE Annals of the History of Computing, March 2011

Challenges and Ideas for IoT

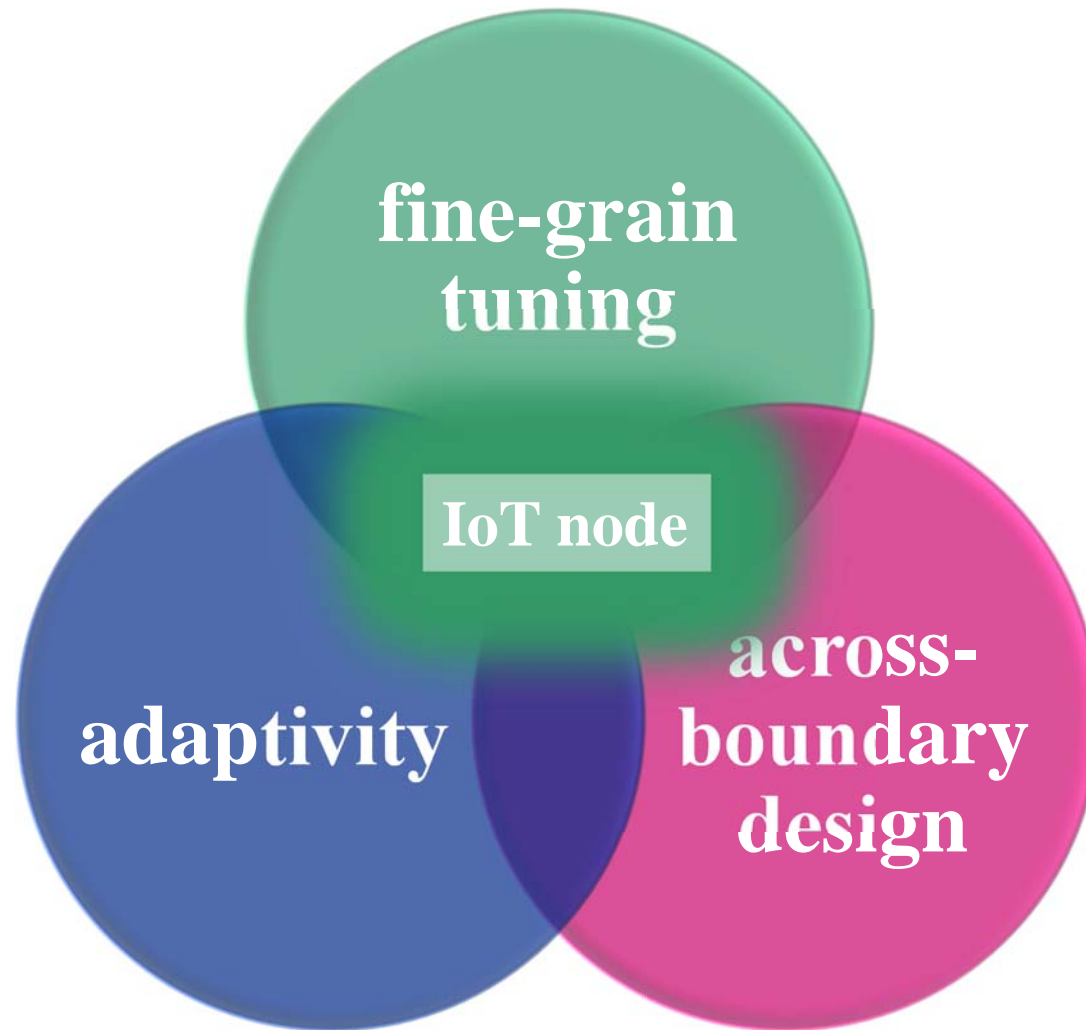
- ◆ IoT needs ultra-low voltage operation
 - ◆ energy vs power, **NT** vs **ST**
- ◆ Ultra-low voltage systems
 - ◆ tighter interaction between levels of abstraction
 - ◆ performance: lower but very sensitive to V_{DD}
 - ◆ **fine-grain** selective voltage boosting
- ◆ Issues and solutions at ULV
 - ◆ performance
 - ◆ NT: recovered architecturally (parallelism, specialized HW, wide voltage scaling)
 - ◆ **across-boundary** design needed (computation vs communication)

◆ leakage

- ◆ sets minimum energy point
- ◆ stacking, power gating, multi- V_{TH} ineffective
- ◆ fine-grain power gating and voltage domains, microarchitecture-circuit co-design, single- V_{TH} selection/body biasing
- ◆ tight interaction of process/circuit/ μ architecture/architecture

◆ variations and resiliency

- ◆ cause large cycle margin (performance/energy penalty)
- ◆ very large at NT/ST
- ◆ across-boundary error detection/correction (cycle-level and sub-cycle), approximate computing
- ◆ $V_{DD,min}$ and **adaptive** techniques to reduce it



THANKS FOR YOUR ATTENTION

Massimo

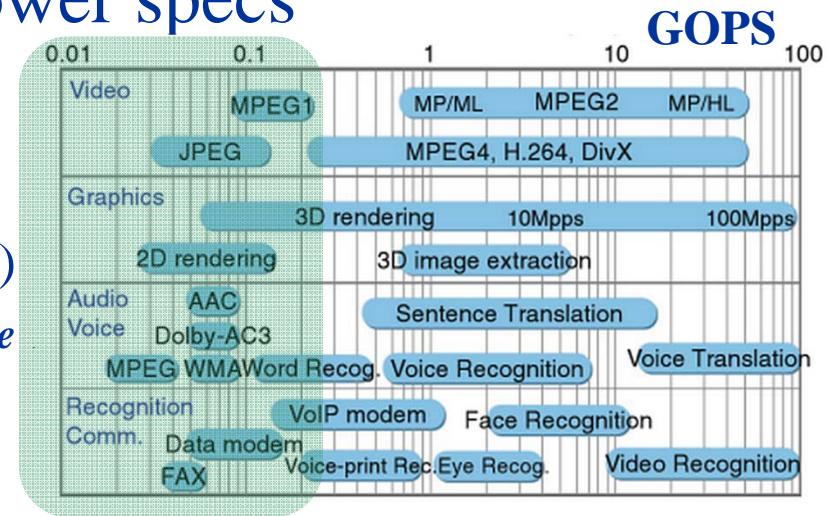


BACKUP SLIDES

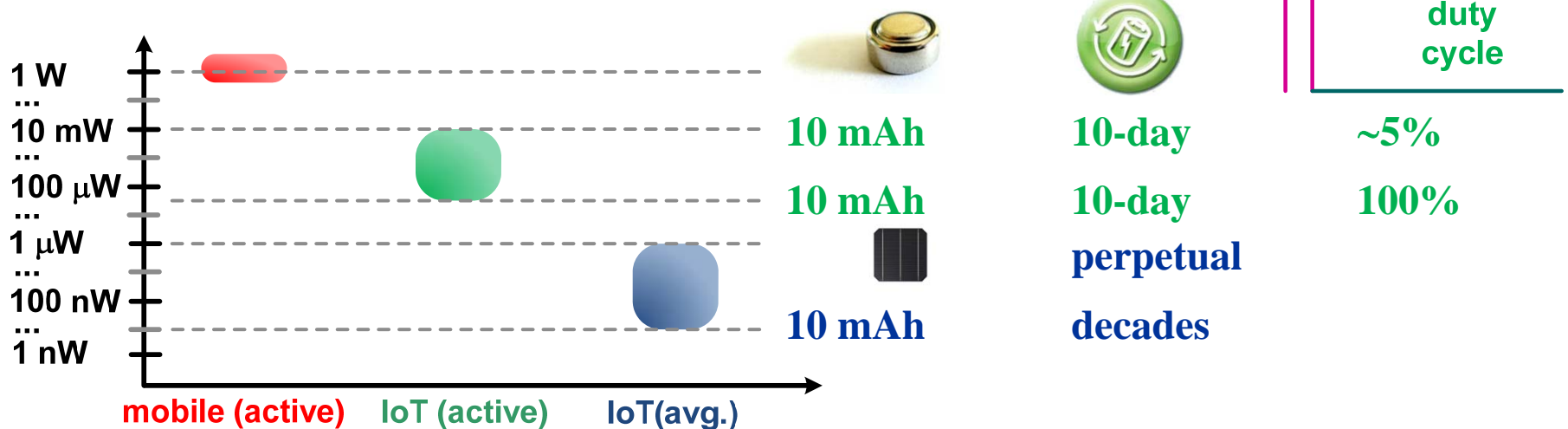
◆ Typical performance and power specs

- ◆ throughput: tens-hundreds of MOPS down to kOPS
(10X slower or more than mobile)

[UAK12] K. Uchiyama, et Al., *Heterogeneous Multicore Technologies for Embedded Systems*, Springer, 2012



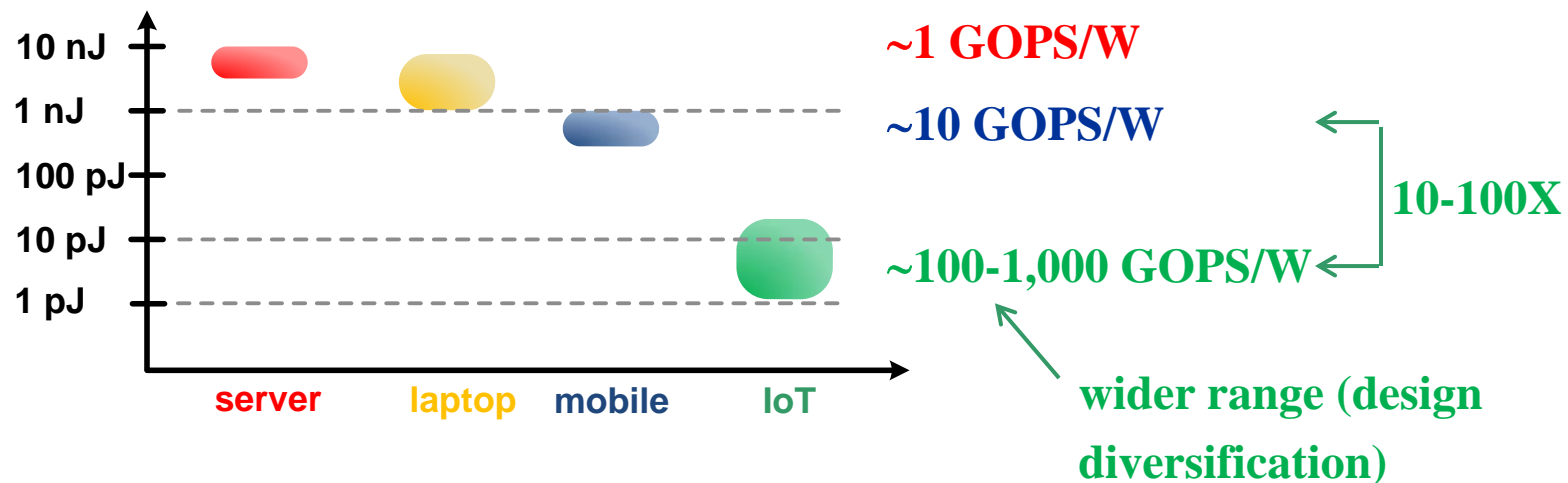
- ◆ power: tens of pJ/op down to few pJ/op



◆ Typical energy range

◆ energy per op:

$$P_{tot} = throughput \cdot E_{op} + P_{static}$$



- ◆ achievable through ULV (5X), architecture tailoring (5-10X), specialized HW (10X) w.r.t. high performance
- ◆ not much gain from technology scaling...